

# Materials and Devices for 3D Integrated Circuits



H.-S. Philip Wong

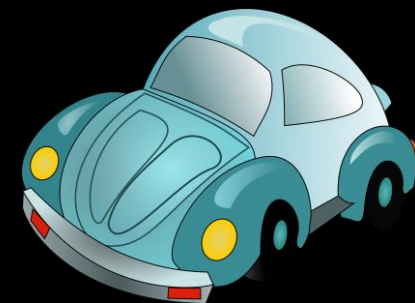
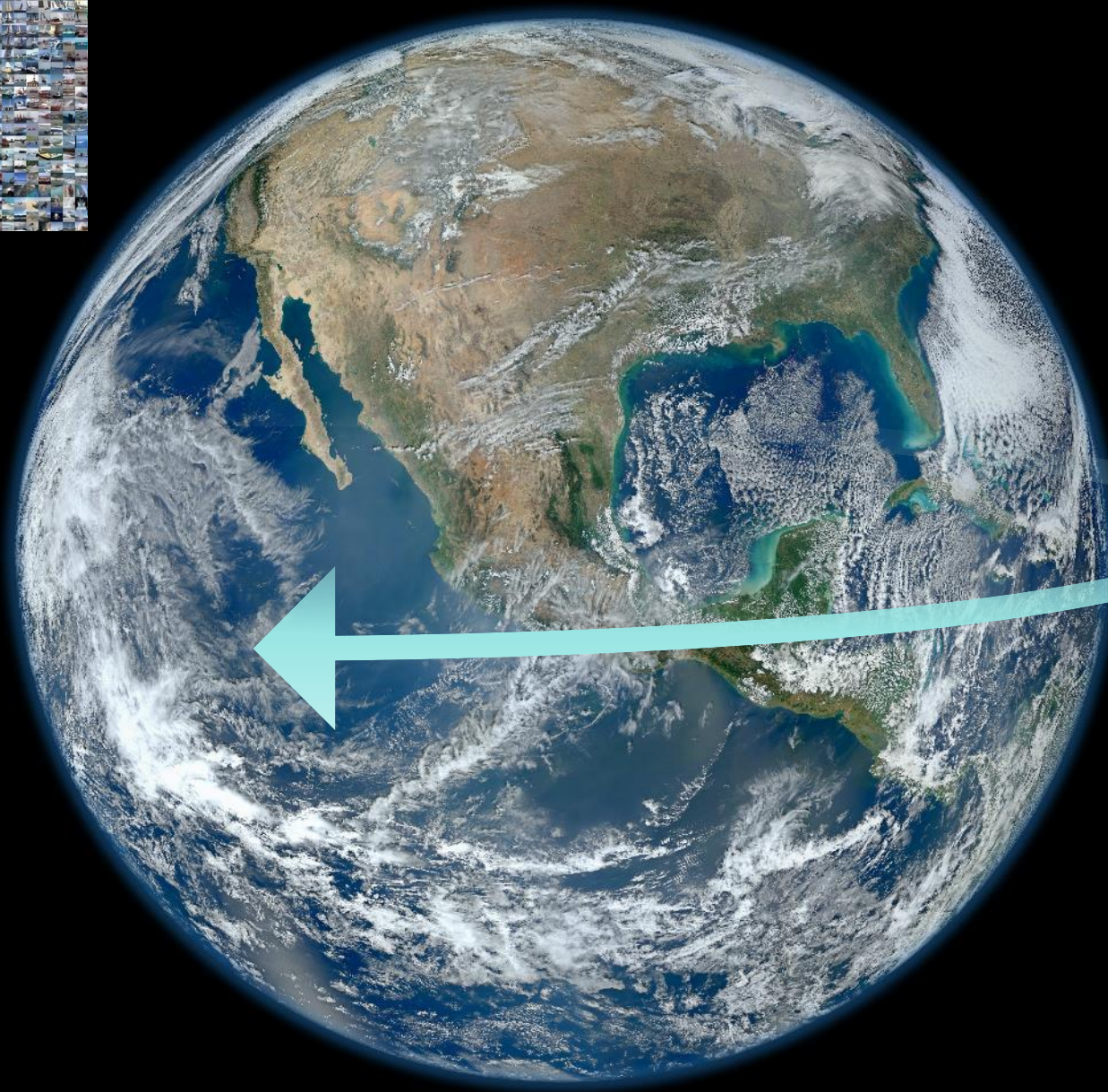
Willard R. & Inez Kerr Bell Professor, Stanford University





Photo by [Andrea Piacquadio](#) from [Pexels](#)





400 times

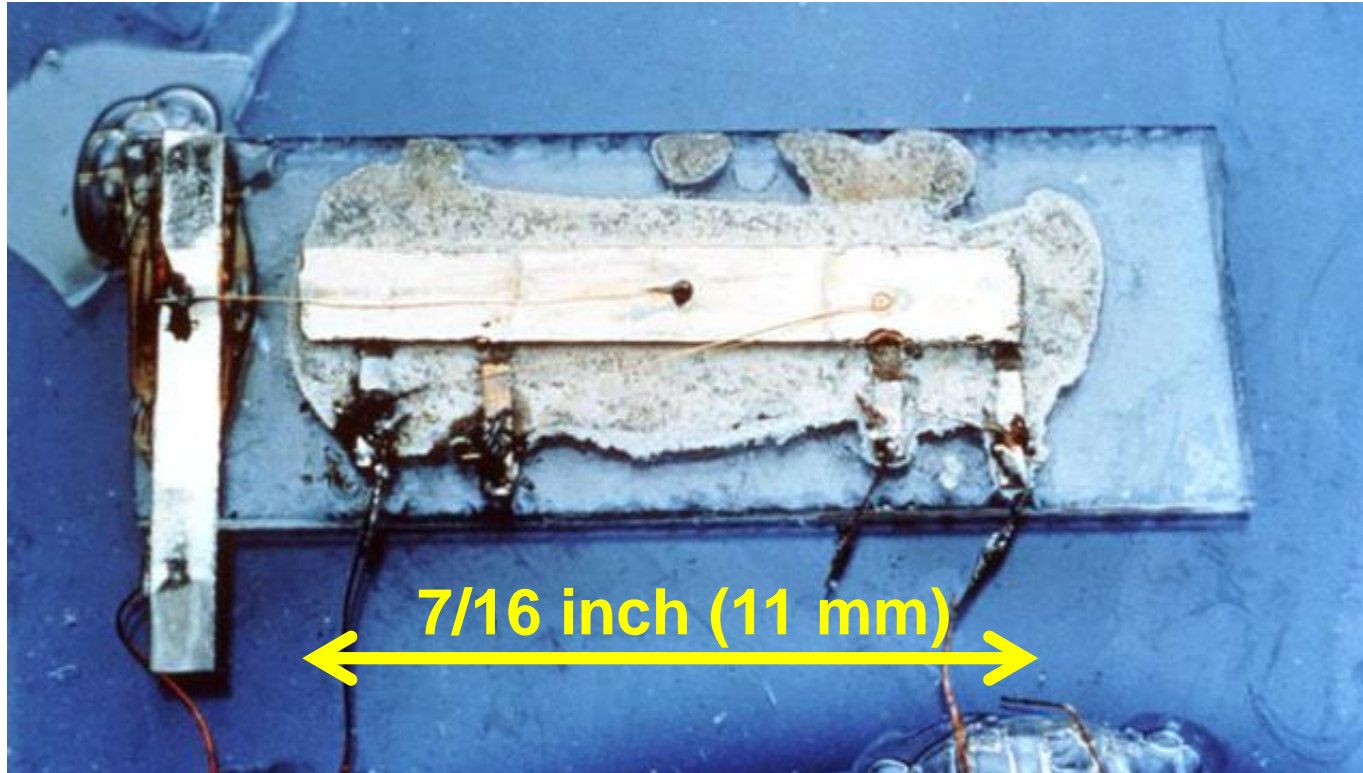




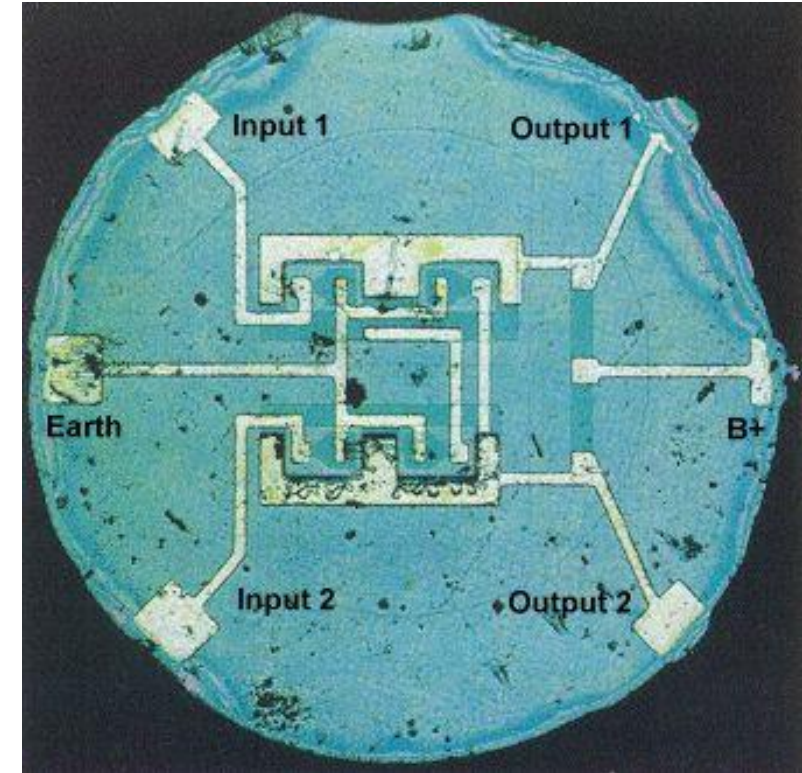
Photo by Akil Mazumder from Pexels



# Integrated Circuit (IC, aka Semiconductor Chips)



**Jack Kilby, 1958**

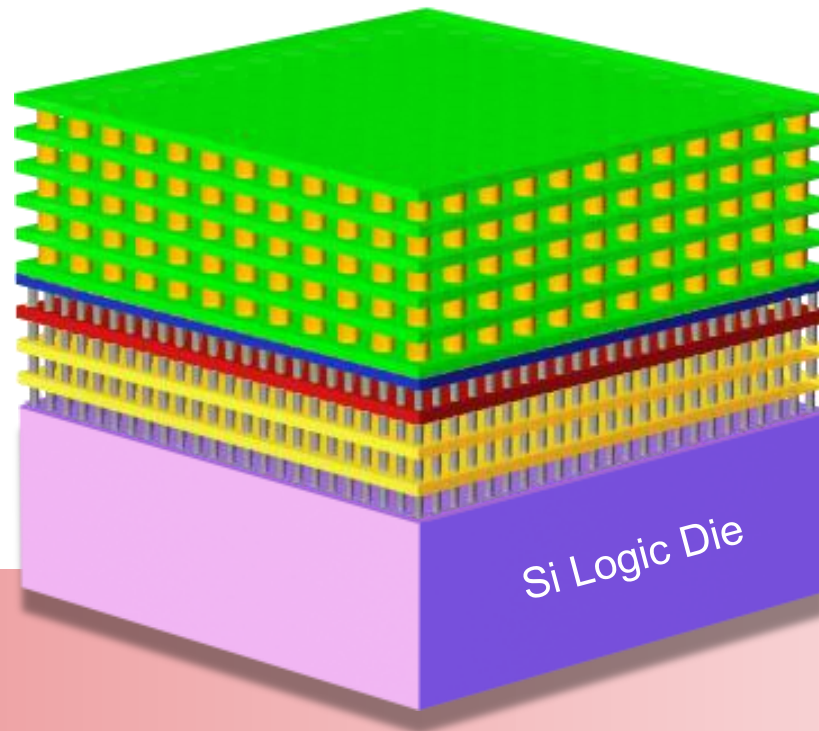


**Robert Noyce, 1959**



# 3D INTEGRATED CIRCUITS

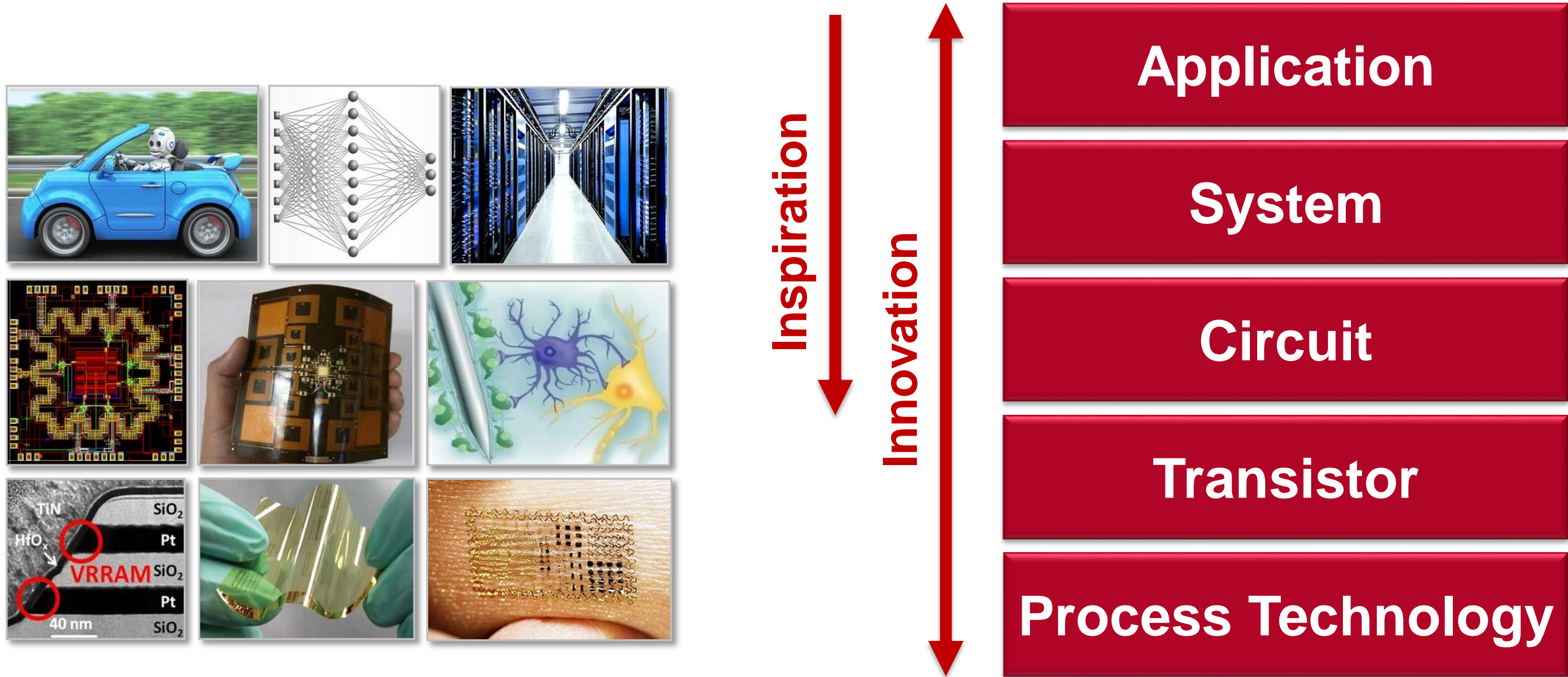
Transistors integrated with memory in **3D**





# Stanford SystemX Alliance

SYSTEM-DRIVEN INNOVATION FOR THE 21<sup>ST</sup> CENTURY



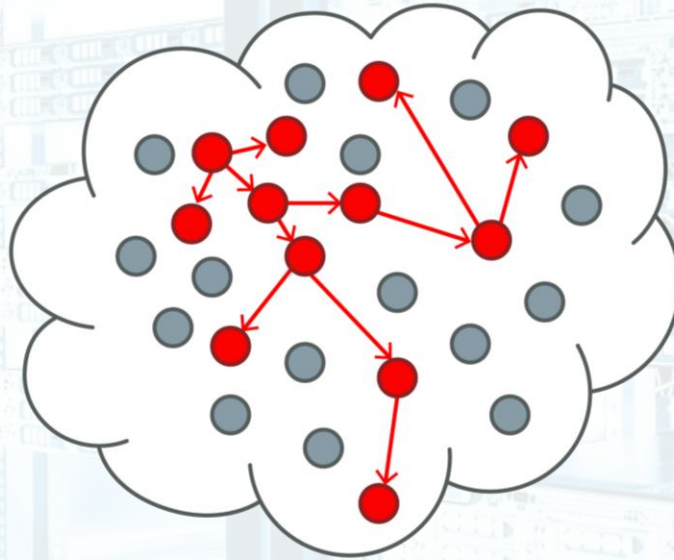
B. Murmann and H.-S. P. Wong, "Vision for a New Era in System Research," Stanford SystemX Alliance inaugural meeting, October 20, 2014



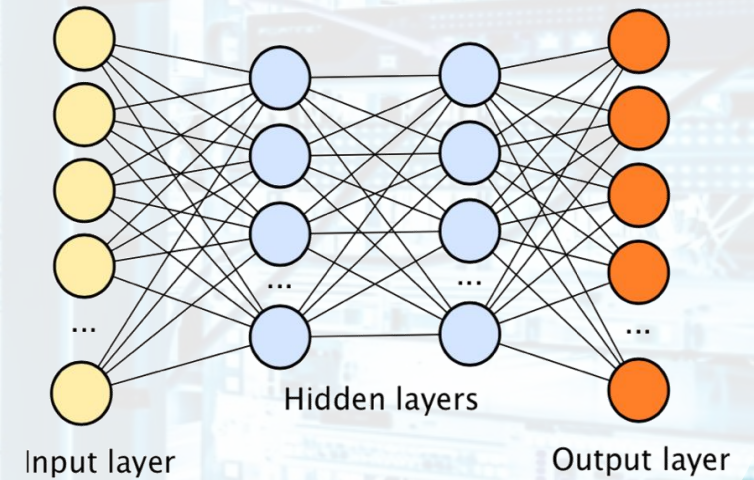
## Big Data



## Graph analytics

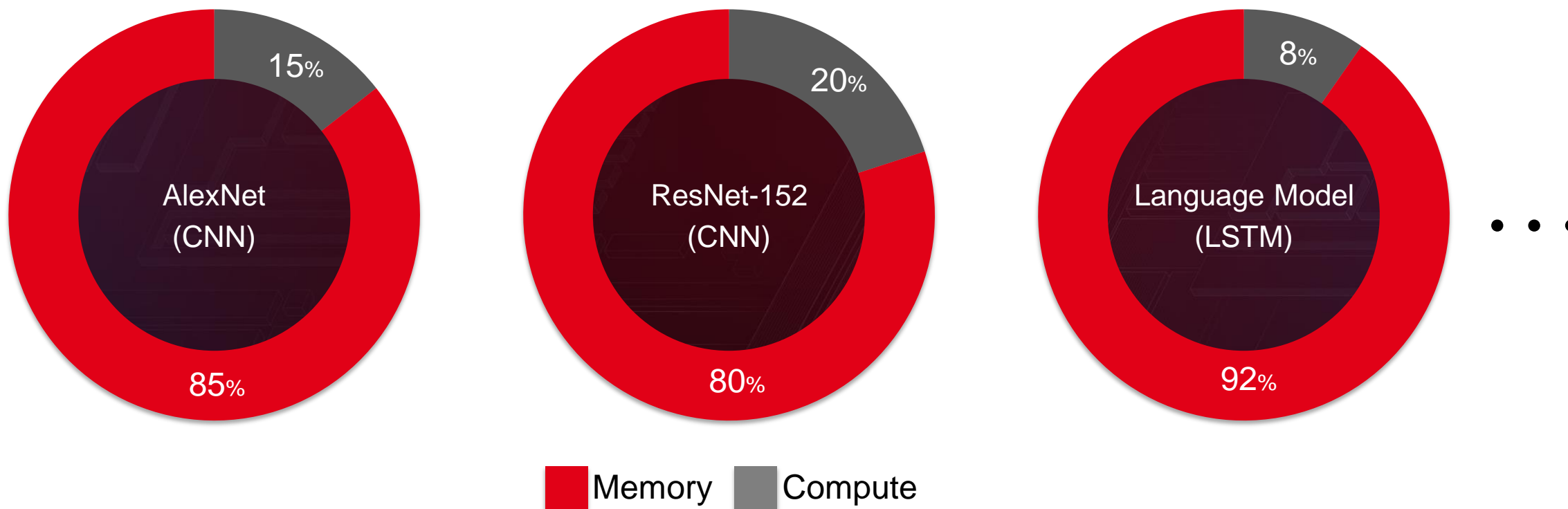


## Machine learning



# DATA MOVEMENT HITS THE MEMORY WALL

ABUNDANT-DATA APPLICATIONS: ENERGY MEASUREMENTS



Deep Learning Accelerators

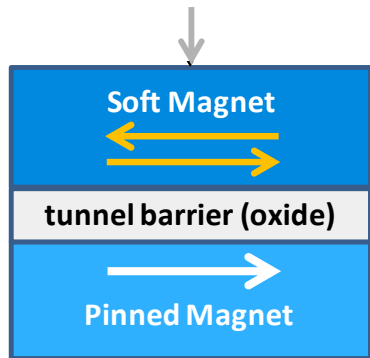
Source: S. Mitra (Stanford)

Intel performance counter monitors 2 CPUs, 8-cores/ CPU + 128GB DRAM



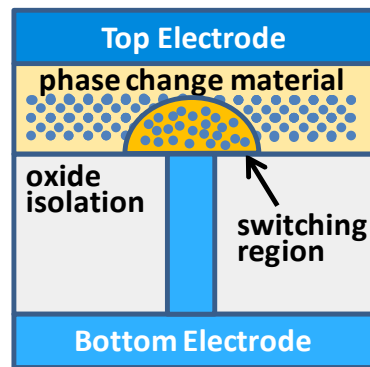
# “NEW” MEMORIES FOR COMPUTE-MEMORY INTEGRATION

Random access, non-volatile, no erase before write, on-chip integration



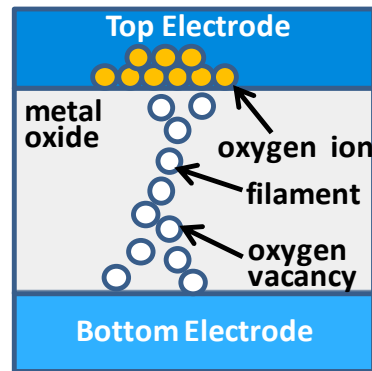
## STT-MRAM

Spin transfer  
torque magnetic  
random access  
memory



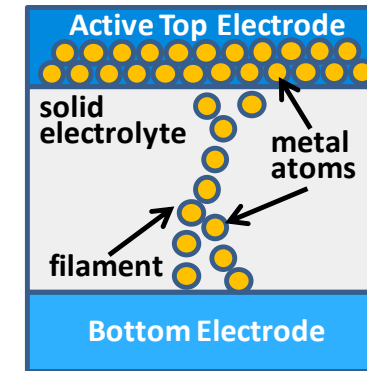
## PCM

Phase change  
memory



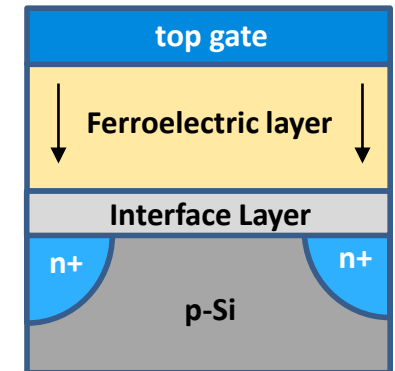
## RRAM

Resistive  
switching random  
access memory



## CBRAM

Conductive  
bridge random  
access  
memory



## FEFET

Ferro-electric  
field effect  
transistor

# PRIMARY IMPORTANCE:

## MEMORY CAPACITY AND BANDWIDTH



### The N3XT Approach to Energy-Efficient Abundant-Data Computing

*This paper enables energy-efficient computing for transformative abundant-data applications through heterogeneous integration of energy-efficient logic devices immersed in dense nonvolatile memory, with fine-grained connectivity in a monolithic 3-D architecture.*

By MOHAMED M. SABRY ALY<sup>1</sup>, TONY F. WU<sup>2</sup>, ANDREW BARTOLO, YASH H. MALVIYA, WILLIAM HWANG<sup>3</sup>, GAGE HILLS<sup>4</sup>, IGOR MARKOV, MARY WOOTTERS<sup>5</sup>, MAX M. SHULAKER<sup>6</sup>, H.-S. PHILIP WONG<sup>1</sup>, *Fellow IEEE*, AND SUBHASISH MITRA<sup>7</sup>, *Fellow IEEE*

Aly et al., *IEEE Proceedings* 2018



### A Density Metric for Semiconductor Technology

By H.-S. PHILIP WONG<sup>1</sup>

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*Stanford University, Stanford, CA 94305 USA*

JAMES D. PLUMMER

*Stanford University, Stanford, CA 94305 USA*

SAYEEF SALAHUDDIN

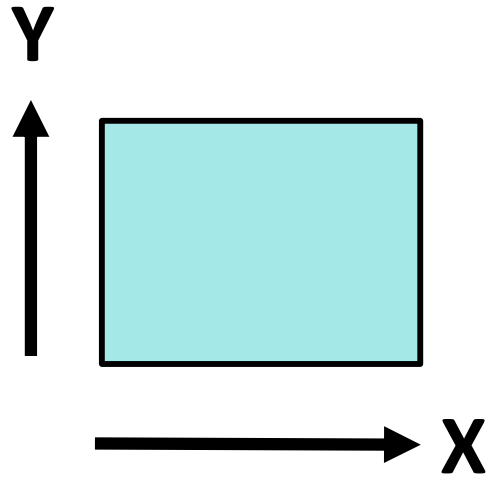
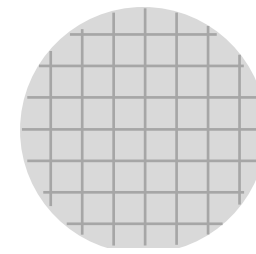
*University of California at Berkeley, Berkeley, CA 94720 USA*

Wong et al., *IEEE Proceedings* 2020

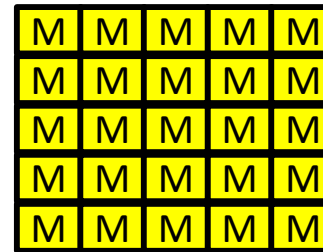


# LARGE MEMORY CAPACITY:

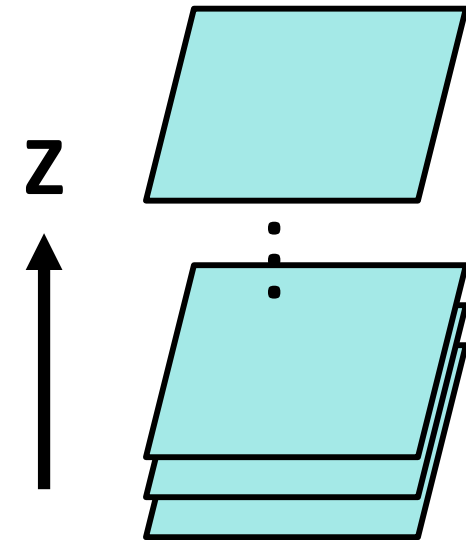
X, Y, Z, M



- Two dimensional down scaling



- Store multiple bits per memory cell

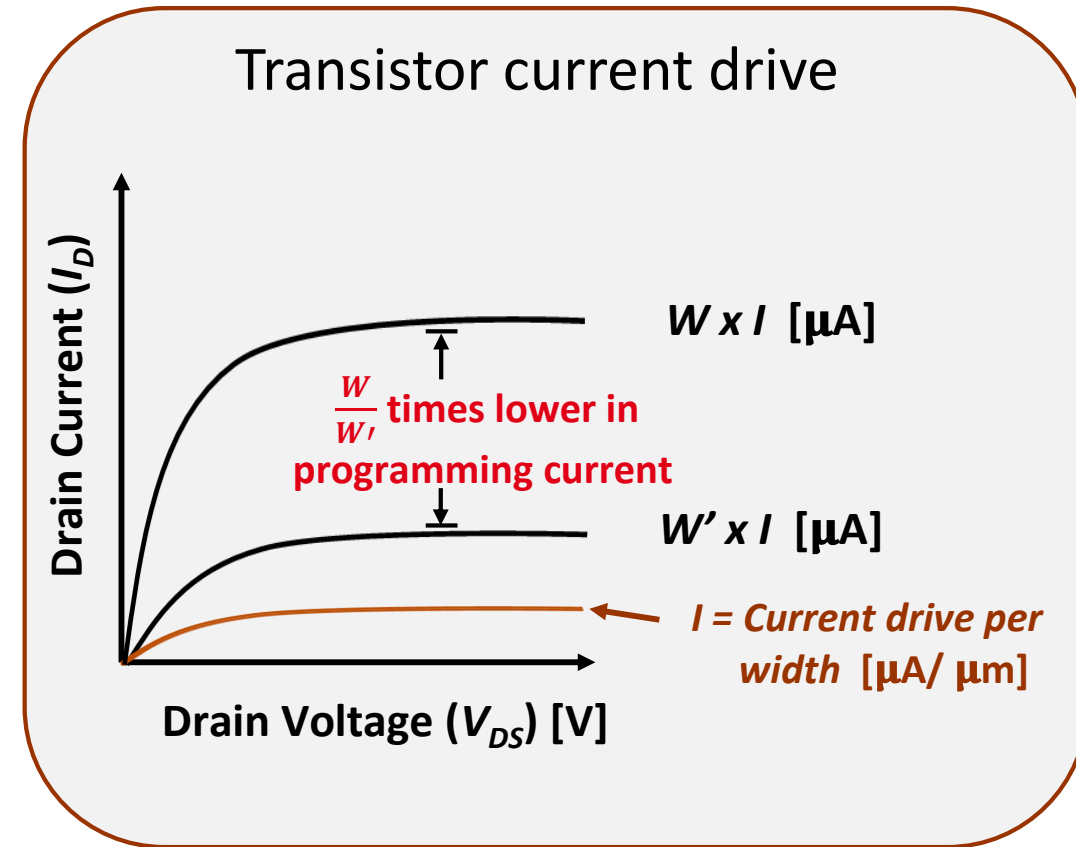
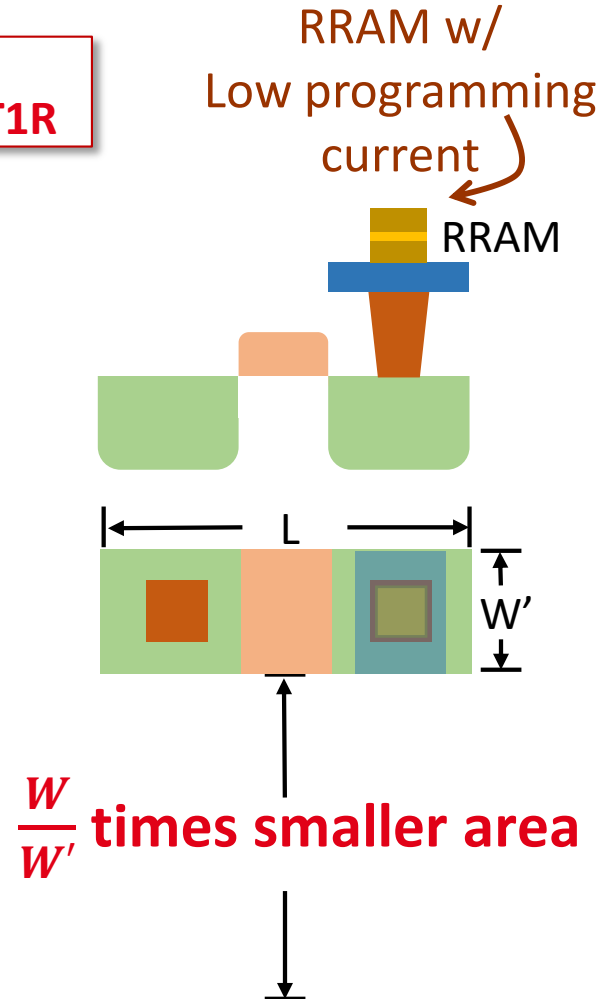
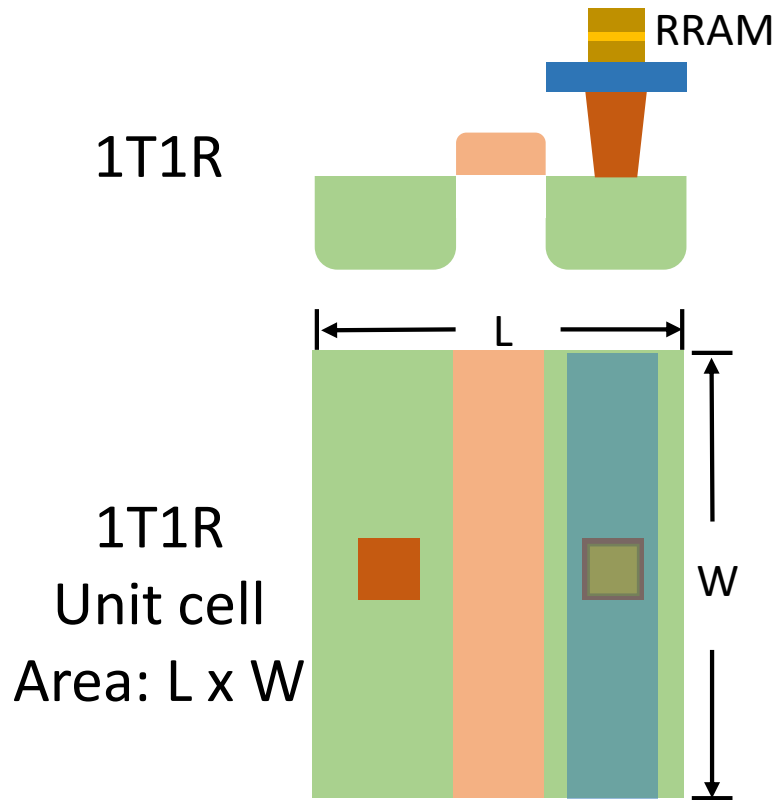


- 3D layers

# MEMORY CELL SIZE:

LIMITED BY TRANSISTOR SIZE

$$\text{Area}_{\text{RRAM}} \ll \text{Area}_{1\text{T}1\text{R}}$$





# HIGHER MEMORY CAPACITY: X, Y, Z, M

Low  
Programming  
Current

< 10  $\mu\text{A}$  programming current  
to achieve dense layout

Multi-bit Cell

$m$ -bit per cell =  $m$  times denser  
(not incl. peripheral circuitry)

Go 3D!

Stack up in the **vertical** direction

# HIGHER MEMORY CAPACITY:

Low  
Programming  
Current

< **10  $\mu\text{A}$**  programming current  
to achieve dense layout

Multi-bit Cell

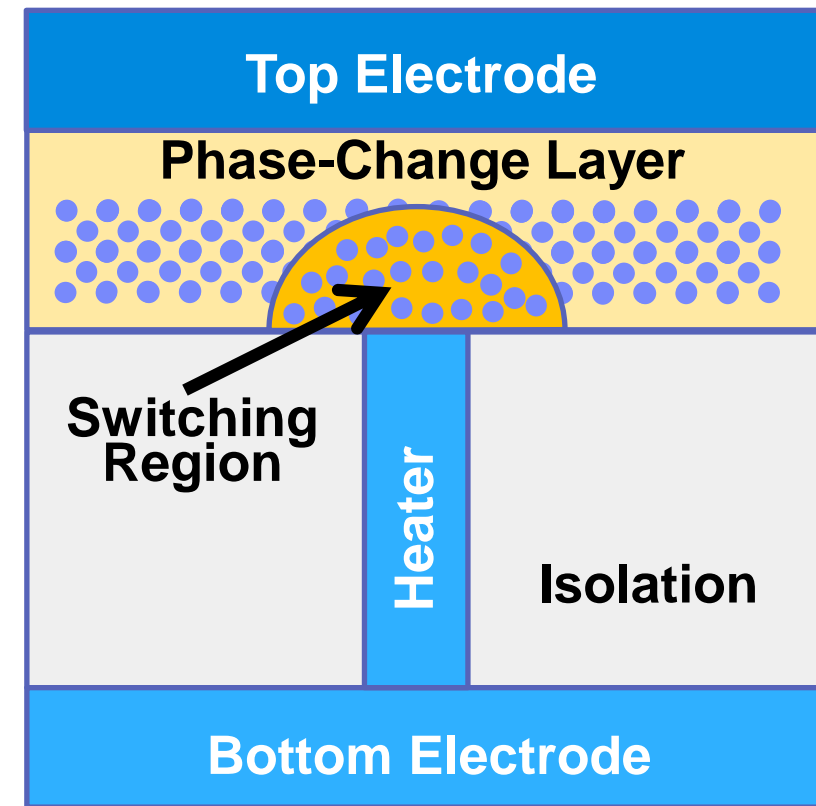
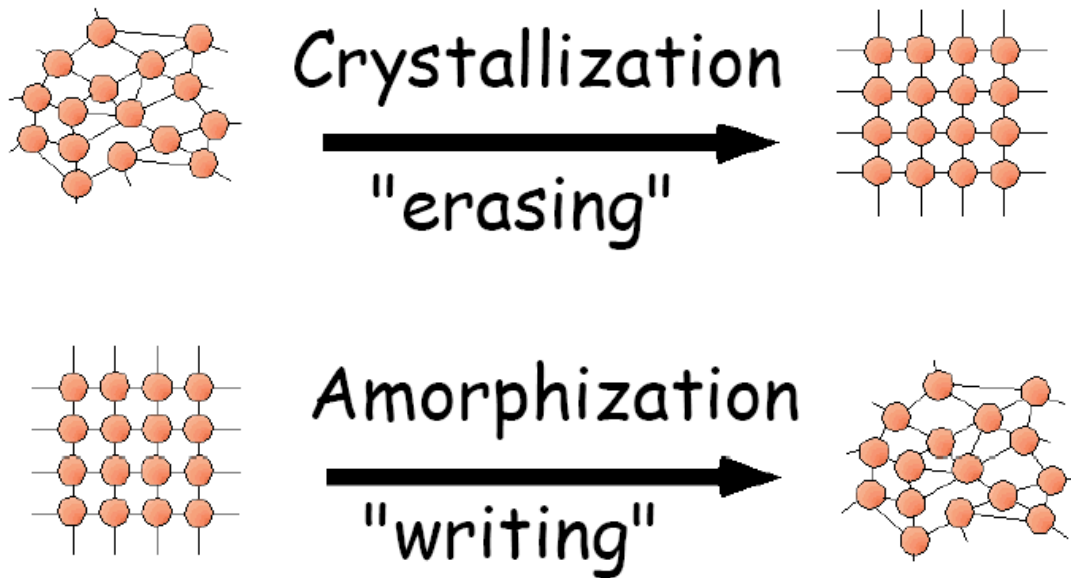
**m-bit per cell** = *m* times denser  
(not incl. peripheral circuitry)

Go 3D!

Stack up in the **vertical** direction

# PCM Switching Physics

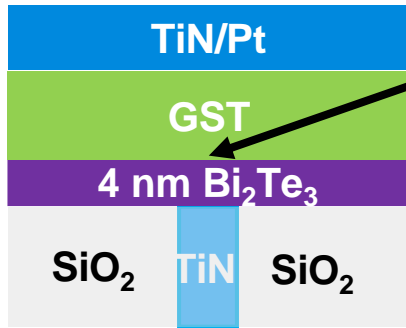
- Writing Mechanism: Current-induced Joule heating
- Amorphization (Reset): Melt and quench ( $T > T_{\text{Melt}}$ )
- Crystallization (Set): Anneal ( $T > T_{\text{crys}}$ )



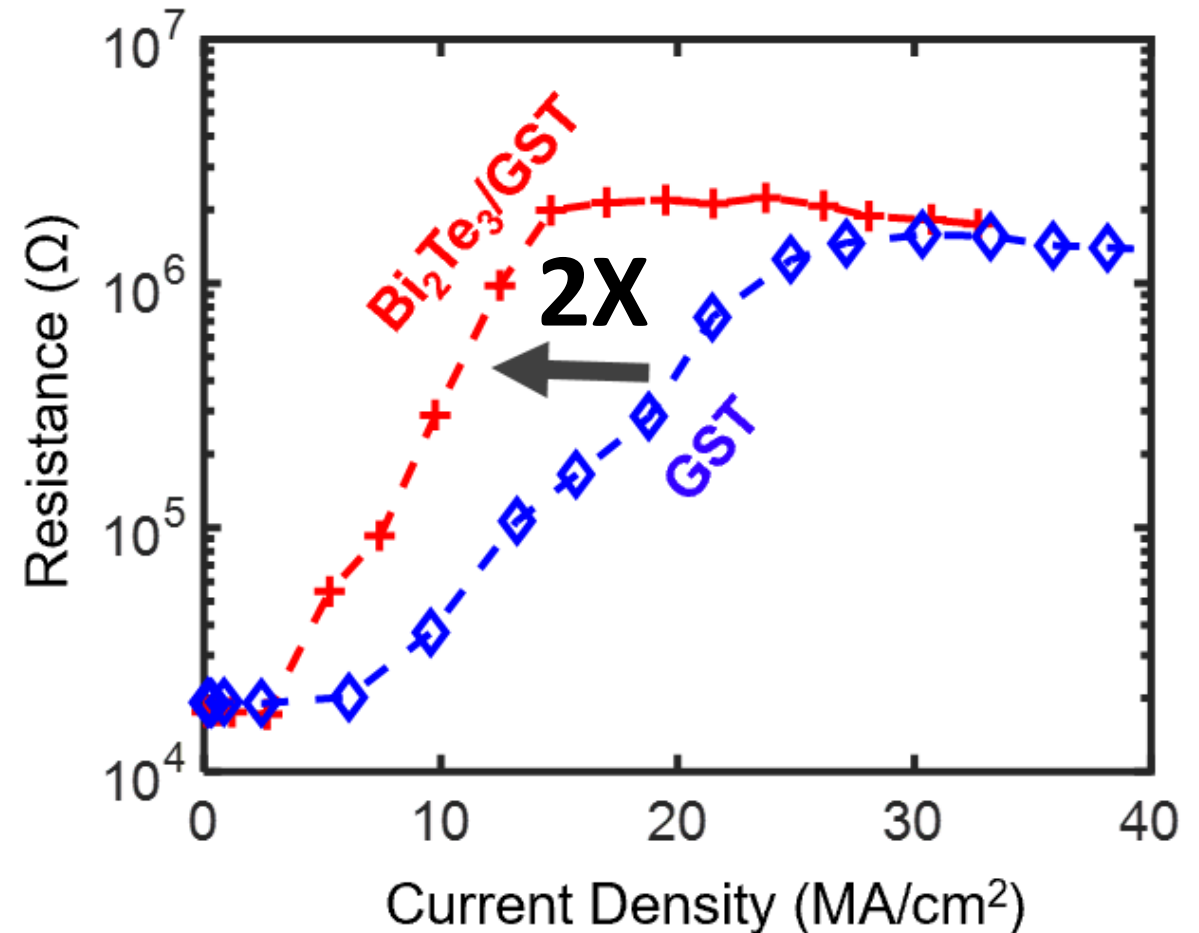
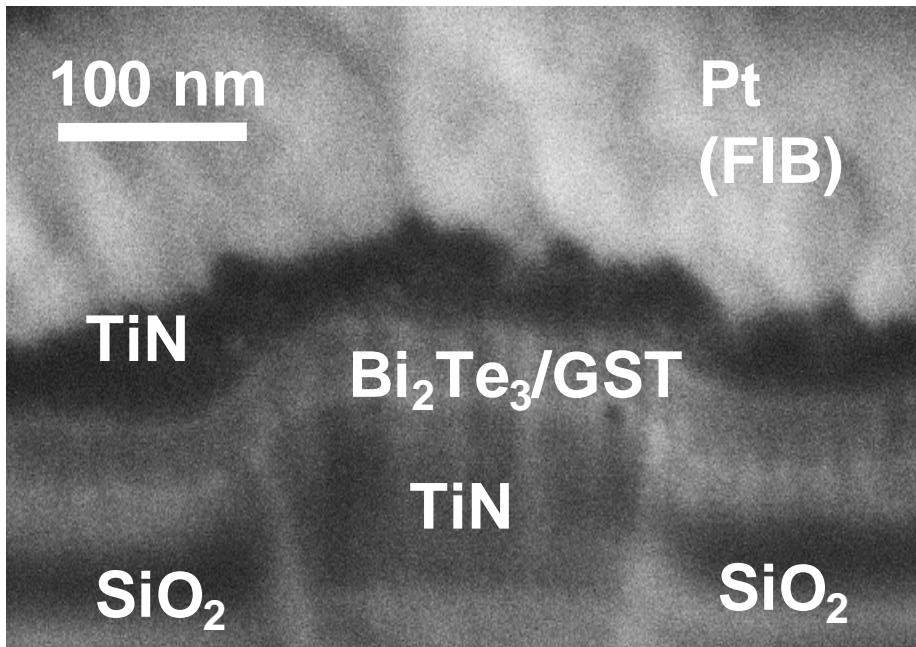
H.-S. P. Wong *et al.*, "Phase Change Memory," *Proc. IEEE* 2010.



# PCM: INTERFACIAL THERMOELECTRIC LAYER ( $\text{Bi}_2\text{Te}_3$ ) – REDUCES $J_{\text{RESET}}$ BY 2X



Thermoelectric effect  
(thin  $\text{Bi}_2\text{Te}_3$  layer) puts  
heat at desired location



# HIGHER MEMORY CAPACITY:

Low  
Programming  
Current

<  $10\ \mu\text{A}$  programming current  
to achieve dense layout

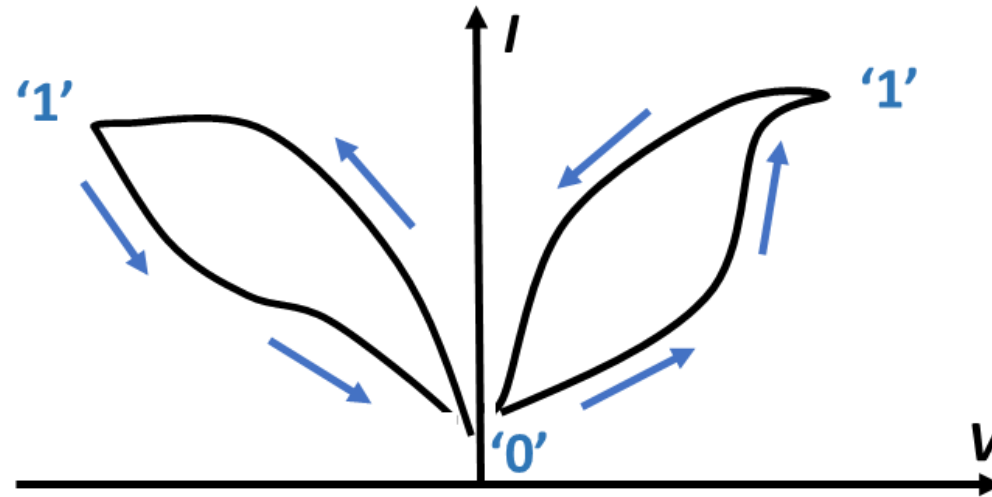
Multi-bit Cell

$m\text{-bit per cell} = m$  times denser  
(not incl. peripheral circuitry)

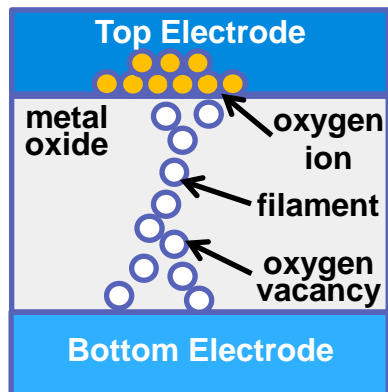
Go 3D!

Stack up in the **vertical** direction

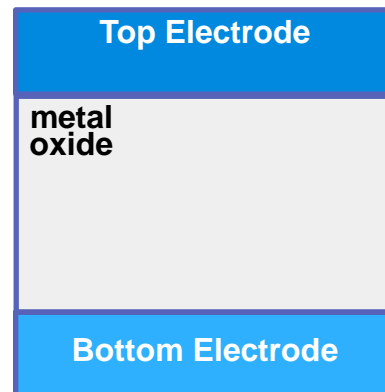
# RRAM: Physics of Resistance Switching



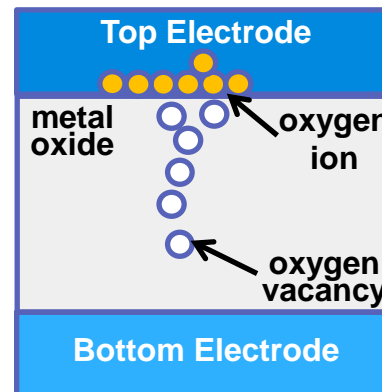
**RRAM**



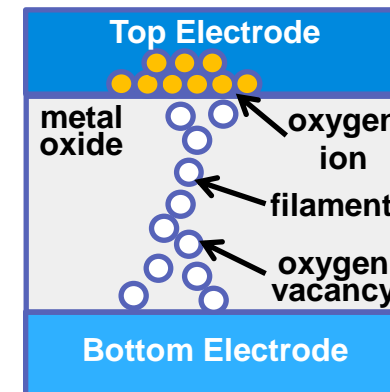
**Pristine "0"**



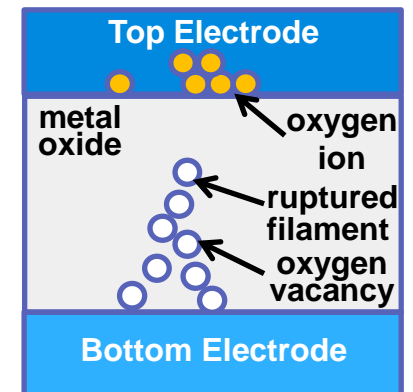
**Set/forming**



**"1"**

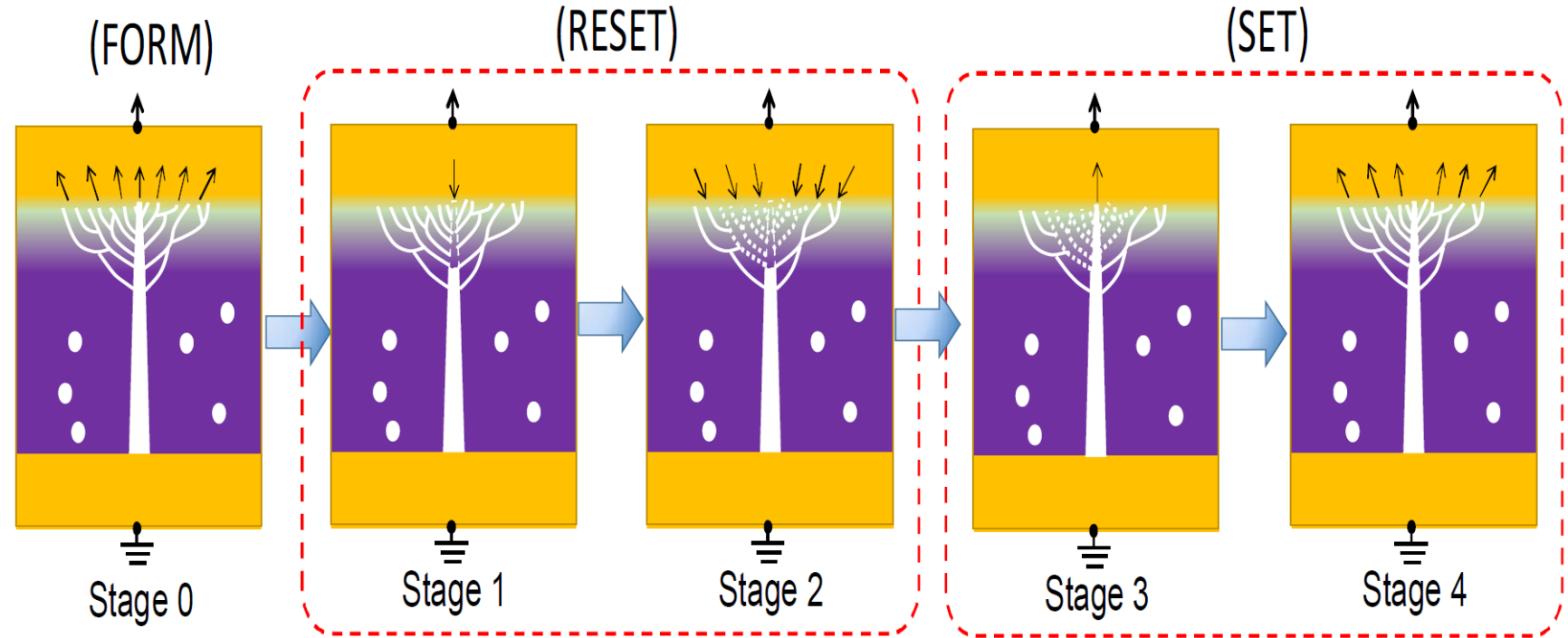
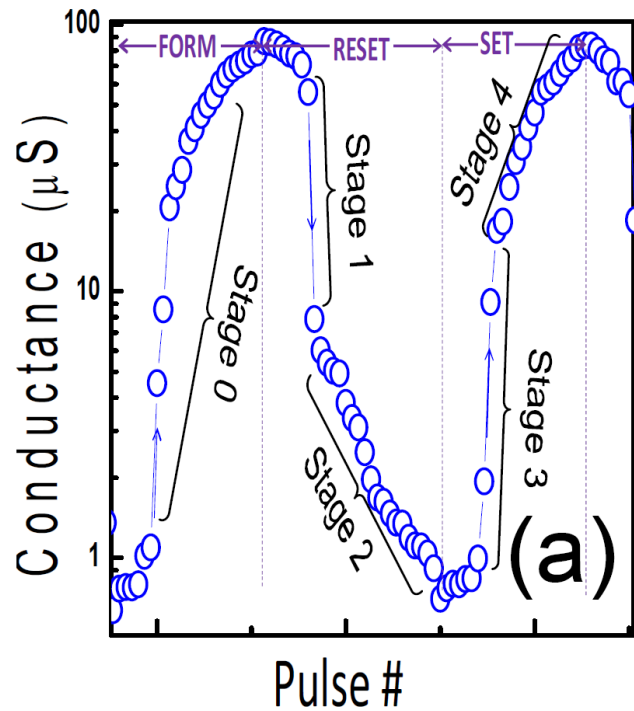


**Reset "0"**

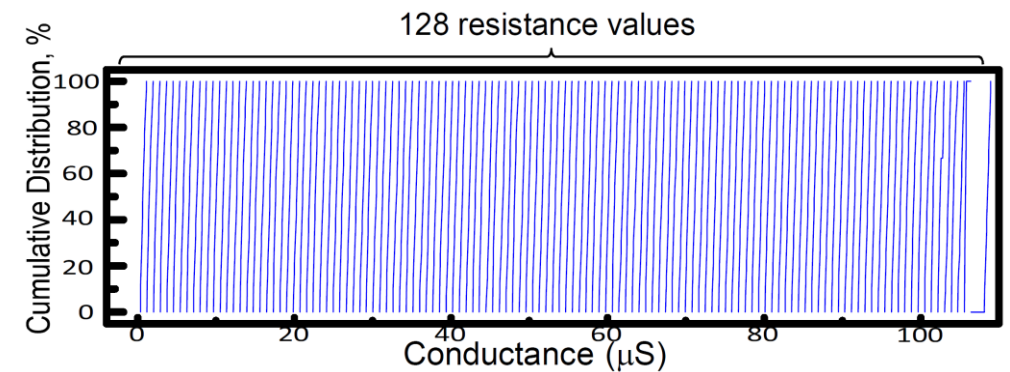
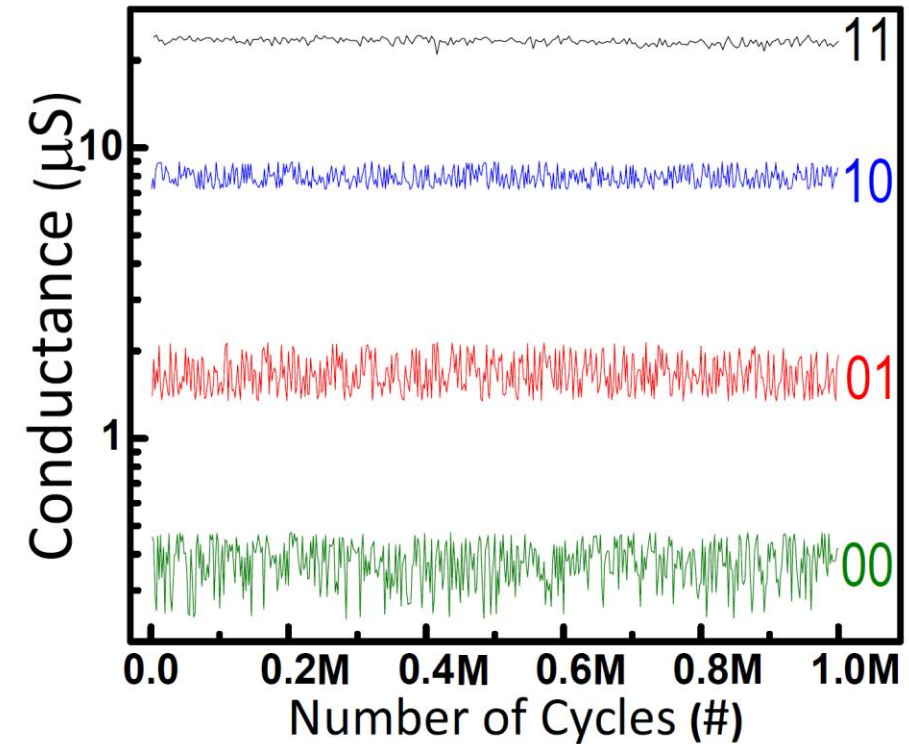
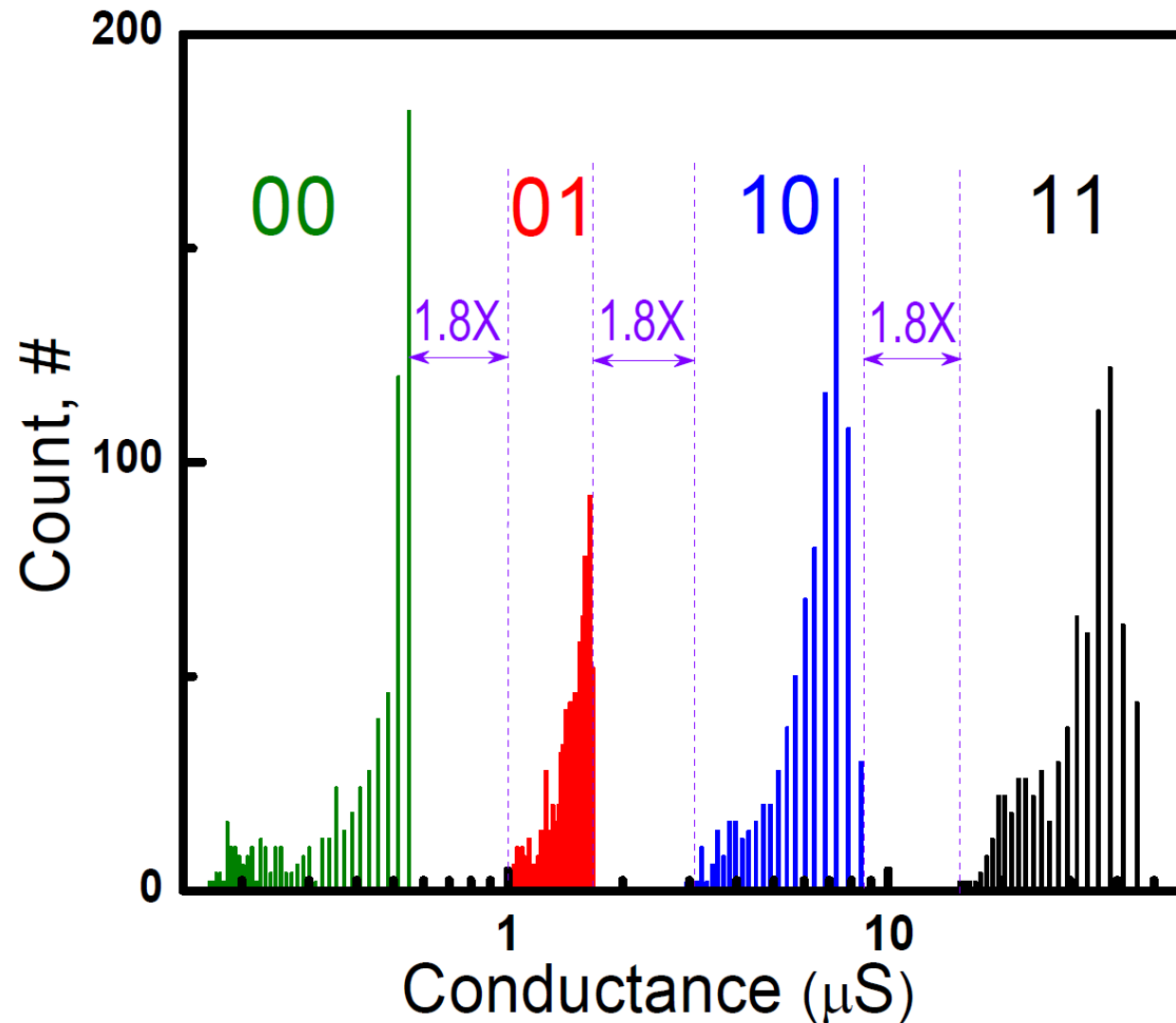




# Multi-bit Resistive Switching Memory (RRAM)



# Multi-bit Resistive Switching Memory (RRAM)



# HIGHER MEMORY CAPACITY:

Low  
Programming  
Current

$< 10 \mu\text{A}$  programming current  
to achieve dense layout

Multi-bit Cell

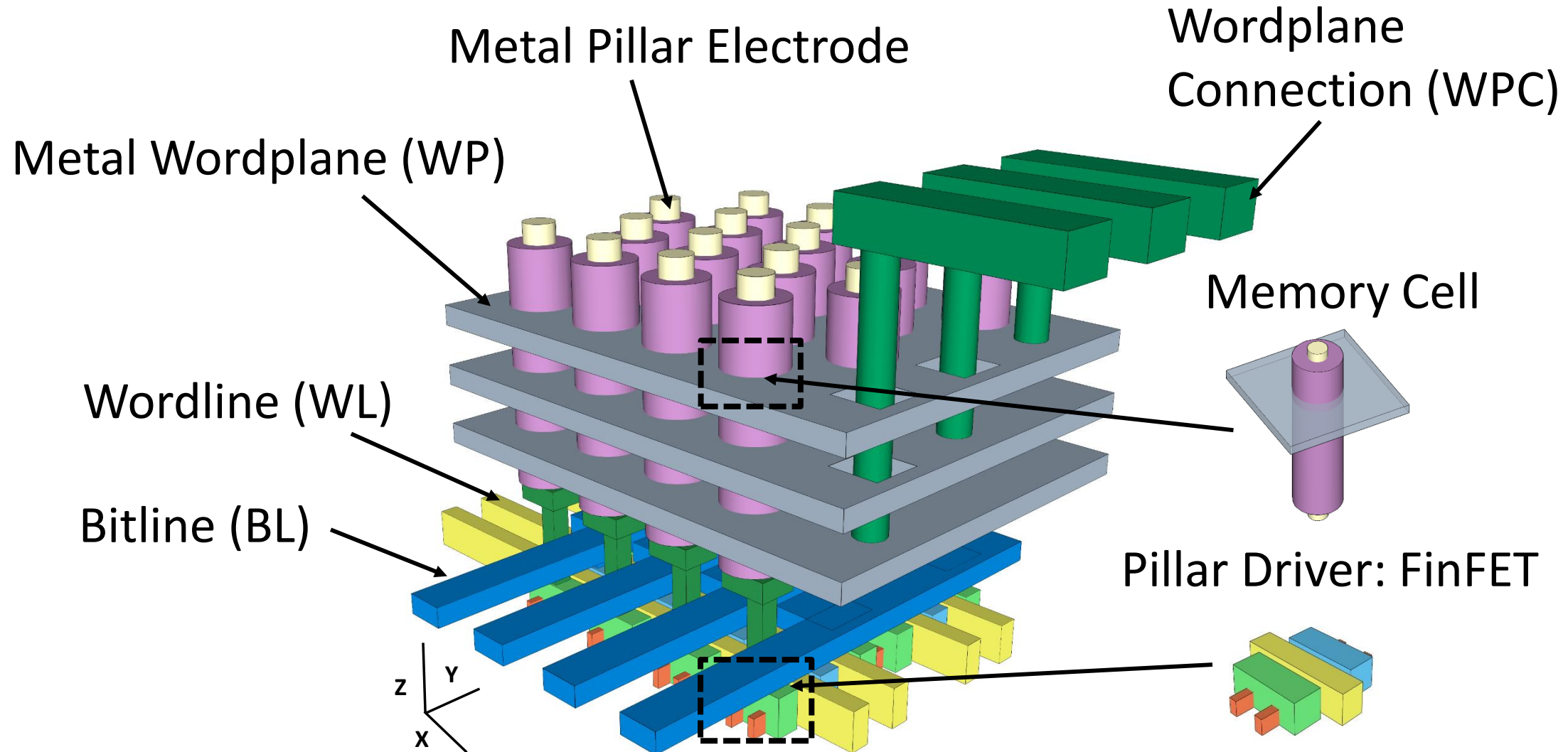
$m\text{-bit per cell} = m$  times denser  
(not incl. peripheral circuitry)

Go 3D!

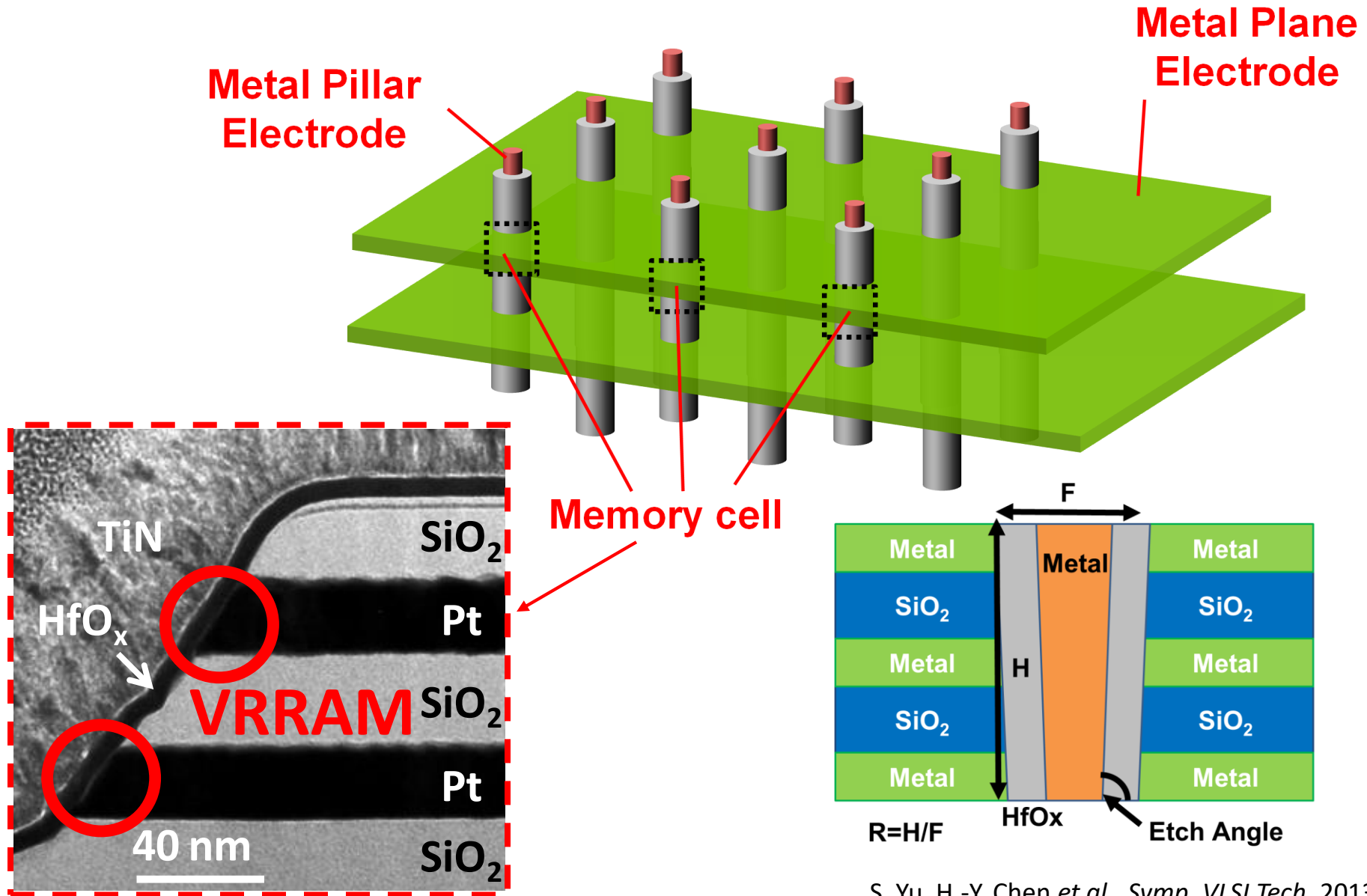
Stack up in the **vertical** direction



# Tbit Class 3D Vertical Resistive Switching Memory



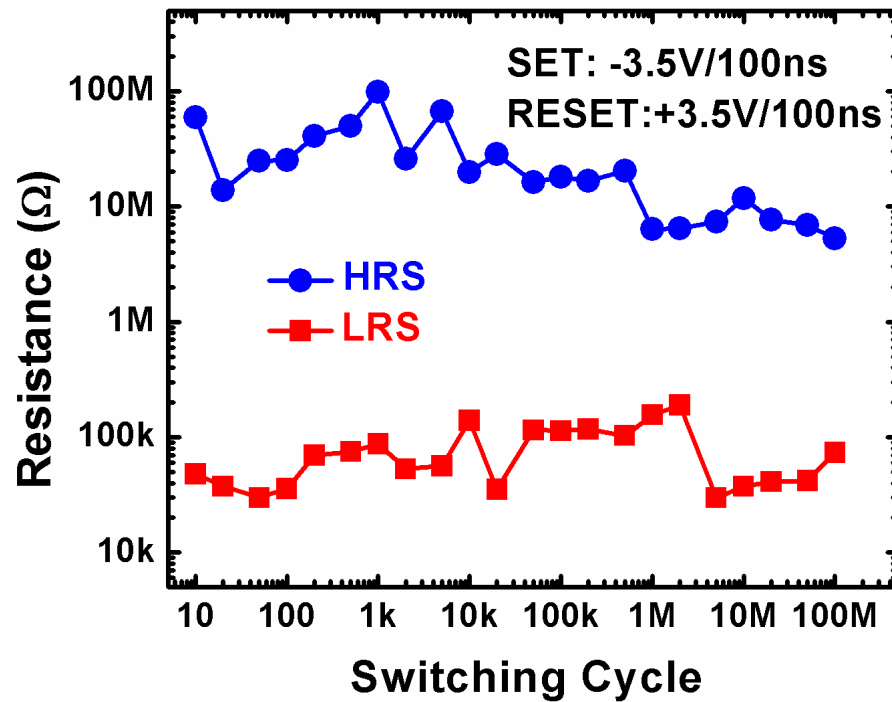
# 3D RRAM



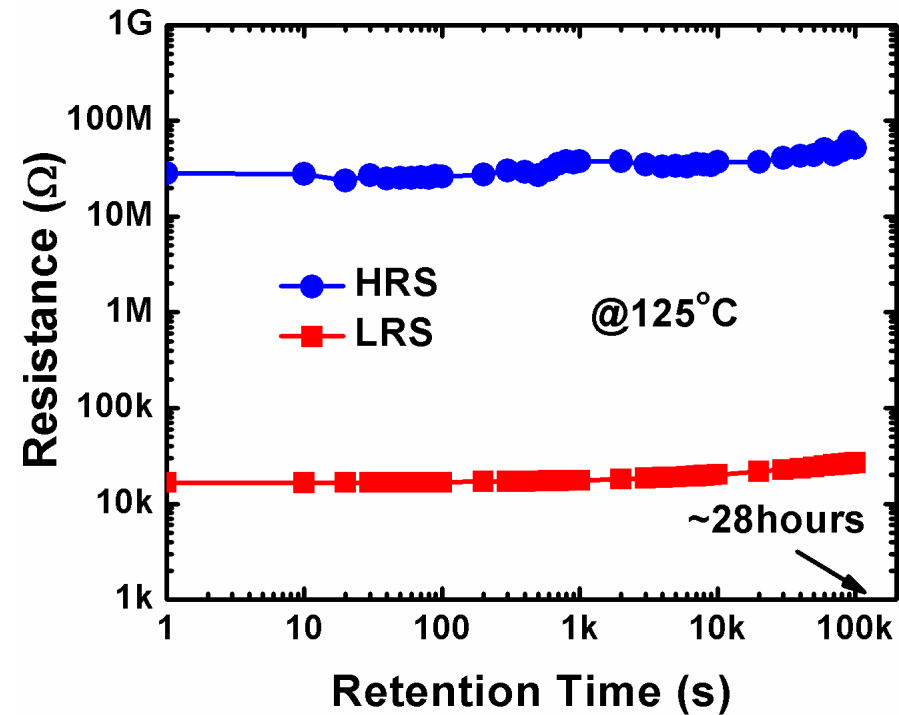
S. Yu, H.-Y. Chen *et al.*, *Symp. VLSI Tech.* 2013

# 3D RRAM – Realistic Performance

Endurance  $>10^8$  cycles



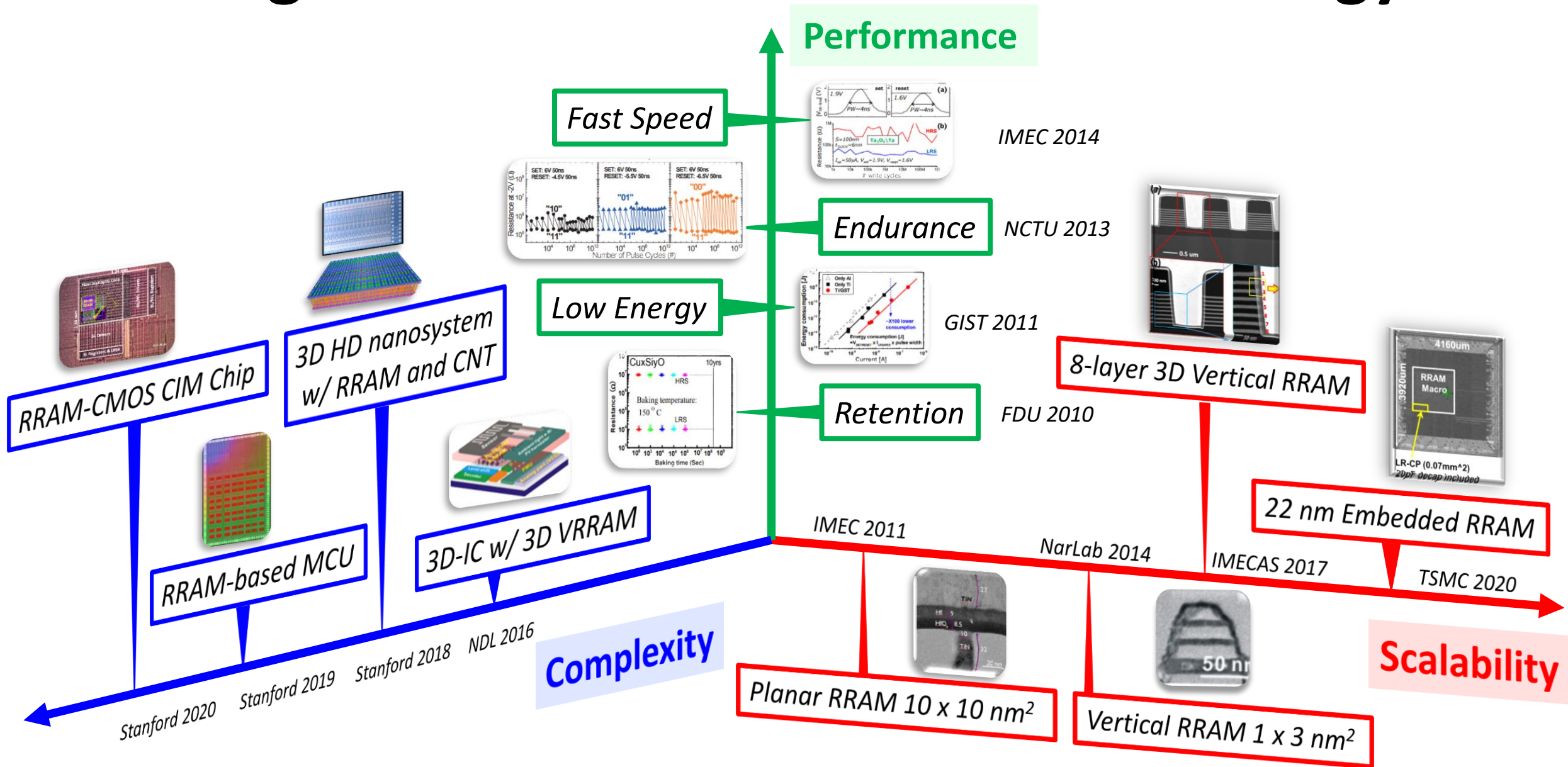
Retention  $>10^5$ s @125°C



H.-Y. Chen *et al.*, IEDM, 2012



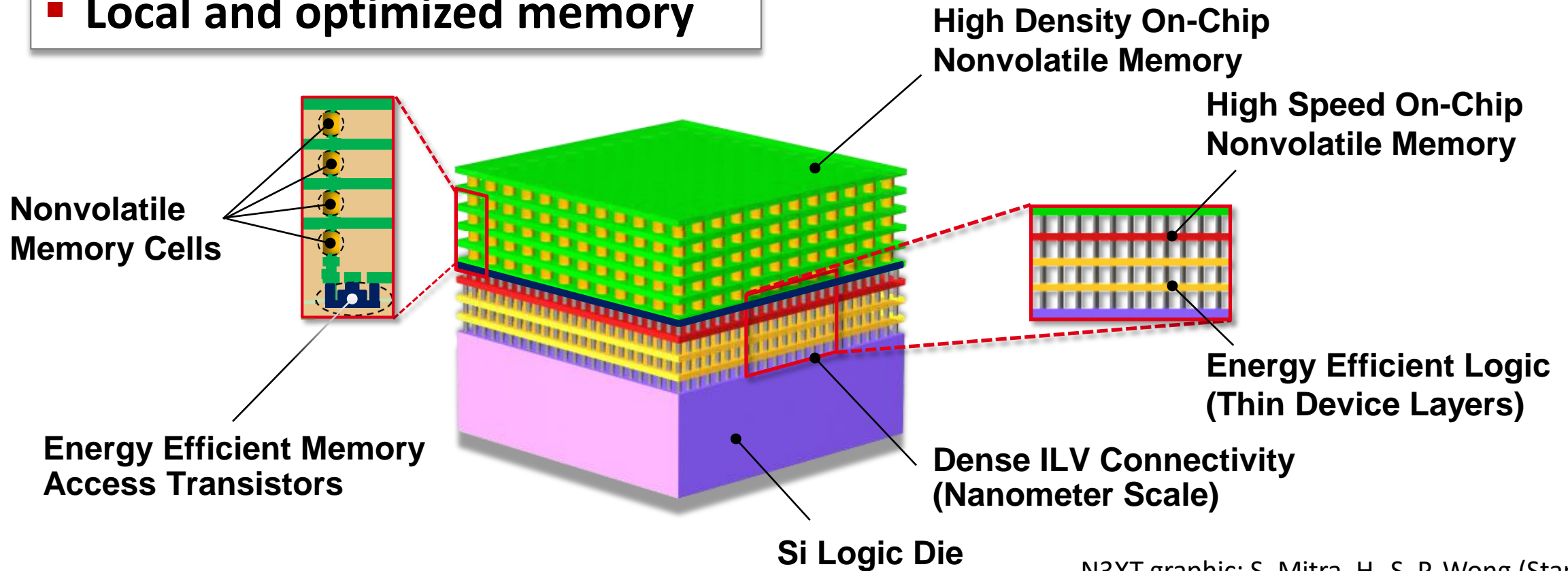
# Progress Towards a Practical Technology



# THE FUTURE IS SYSTEM INTEGRATION

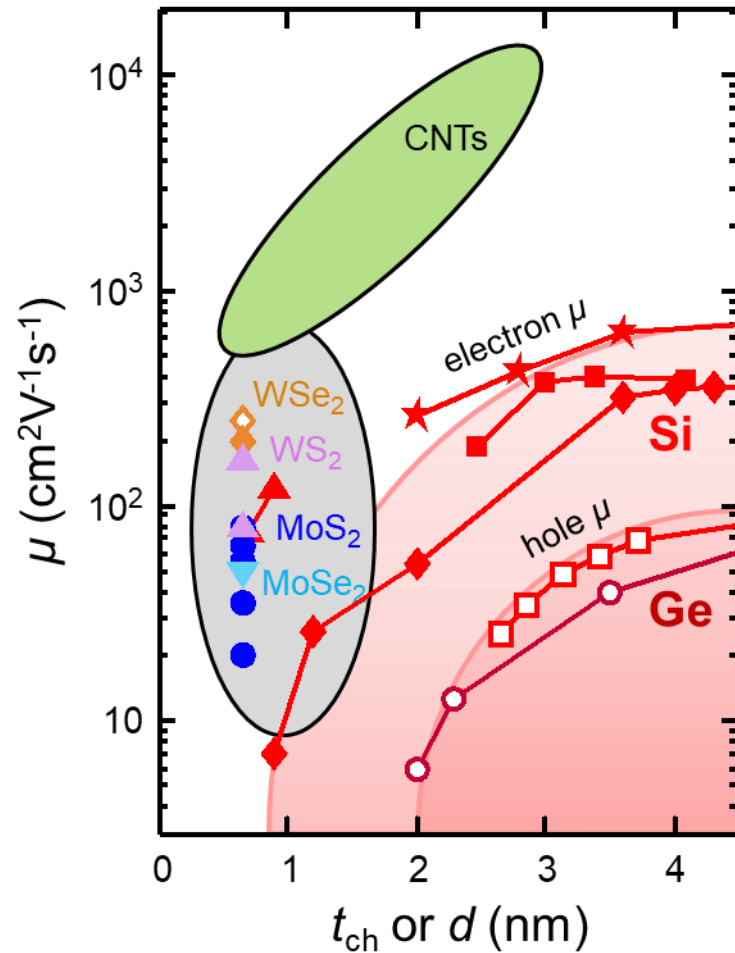
## MEMORY INTEGRATED WITH ENERGY-EFFICIENT TRANSISTORS

- High capacity on-chip memory
- Local and optimized memory

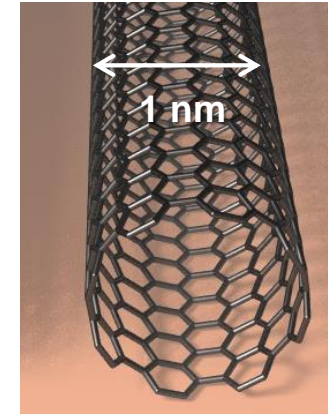


N3XT graphic: S. Mitra, H.-S. P. Wong (Stanford)

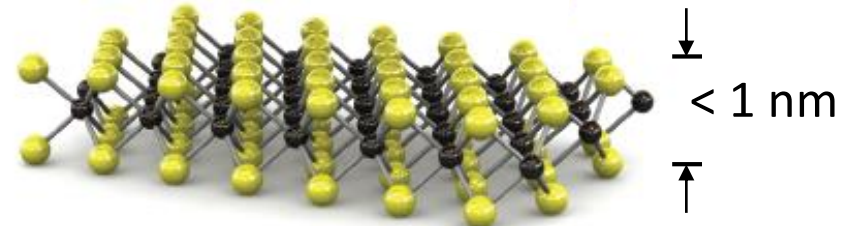
# NANOMETER-THIN TRANSISTOR CHANNEL



1D carbon nanotube (CNT)

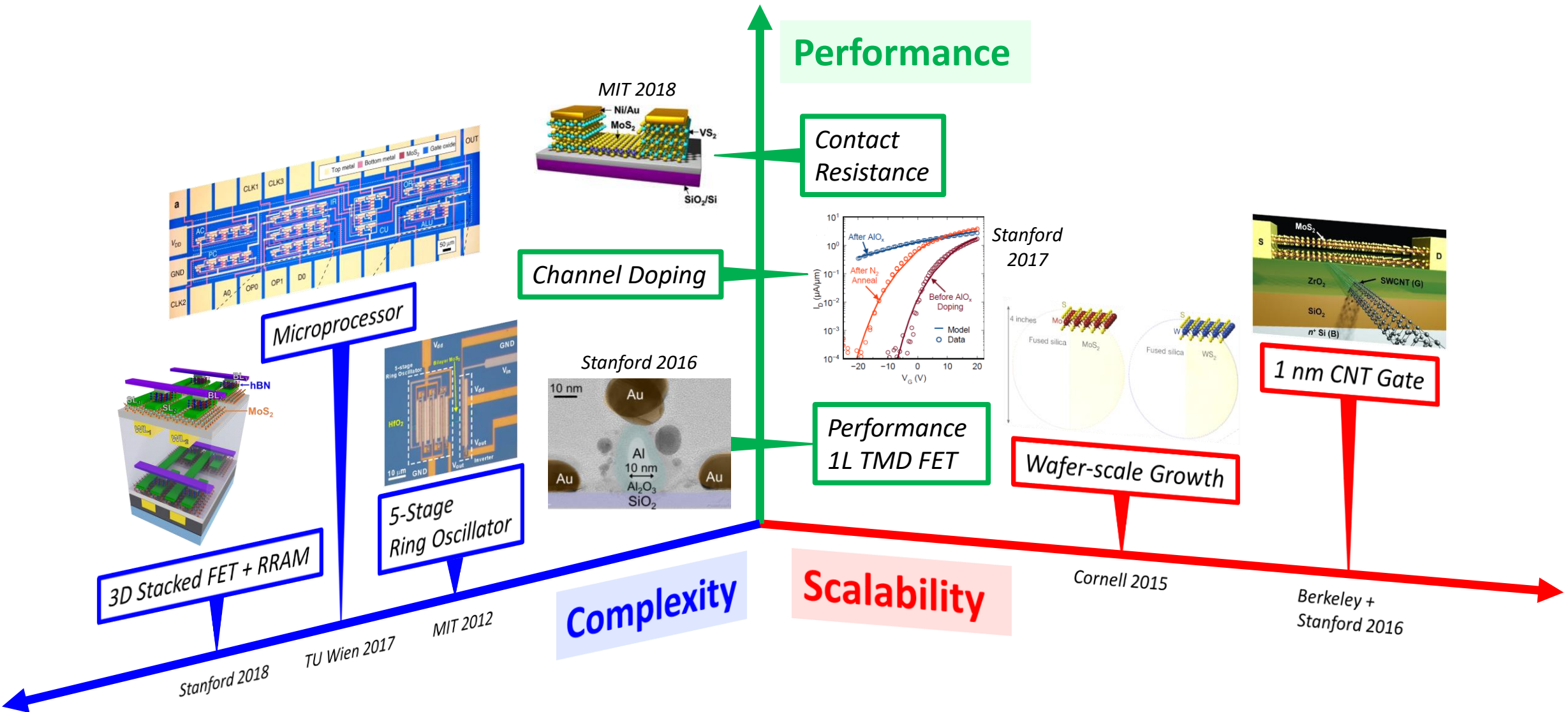


2D Layered Materials  
e.g. Transition Metal Dichalcogenides  
(TMD:  $\text{MoS}_2$ ,  $\text{WS}_2$ ,  $\text{WSe}_2$ ,  $\text{WTe}_2$ , ...), BP, aGNR



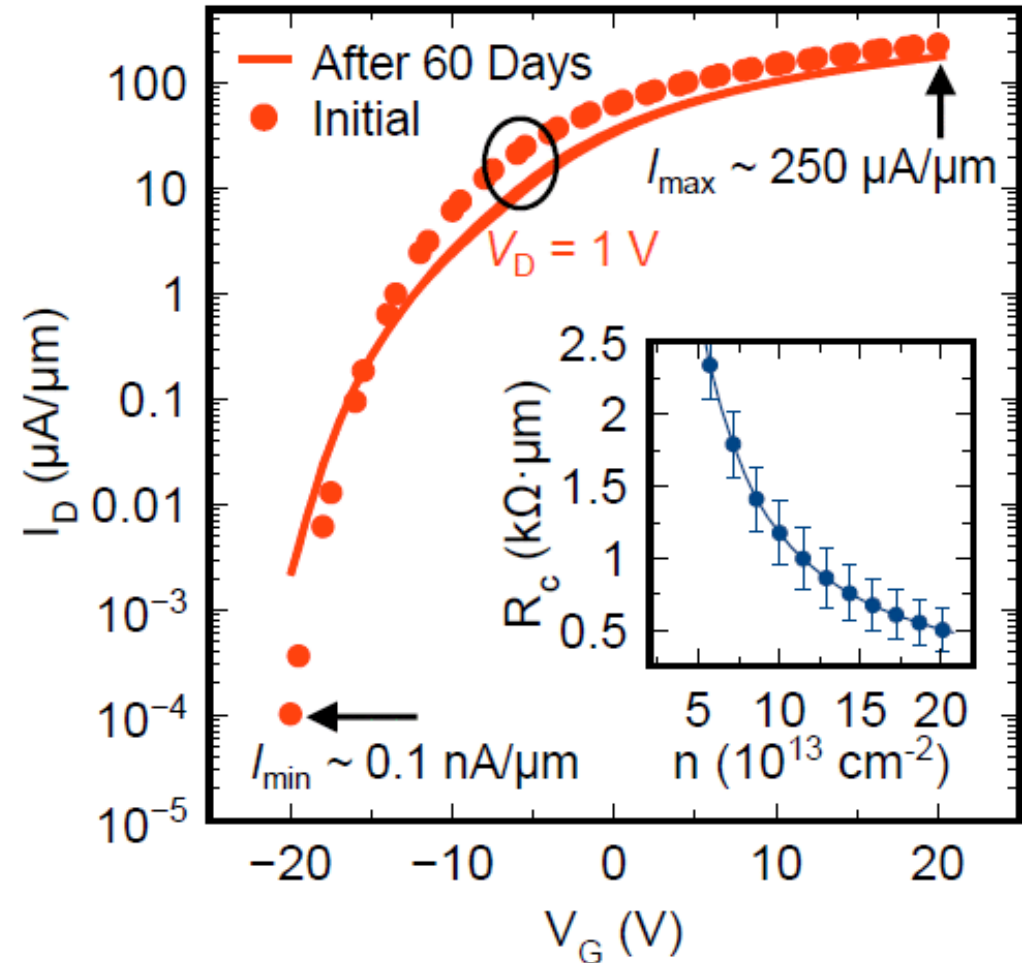
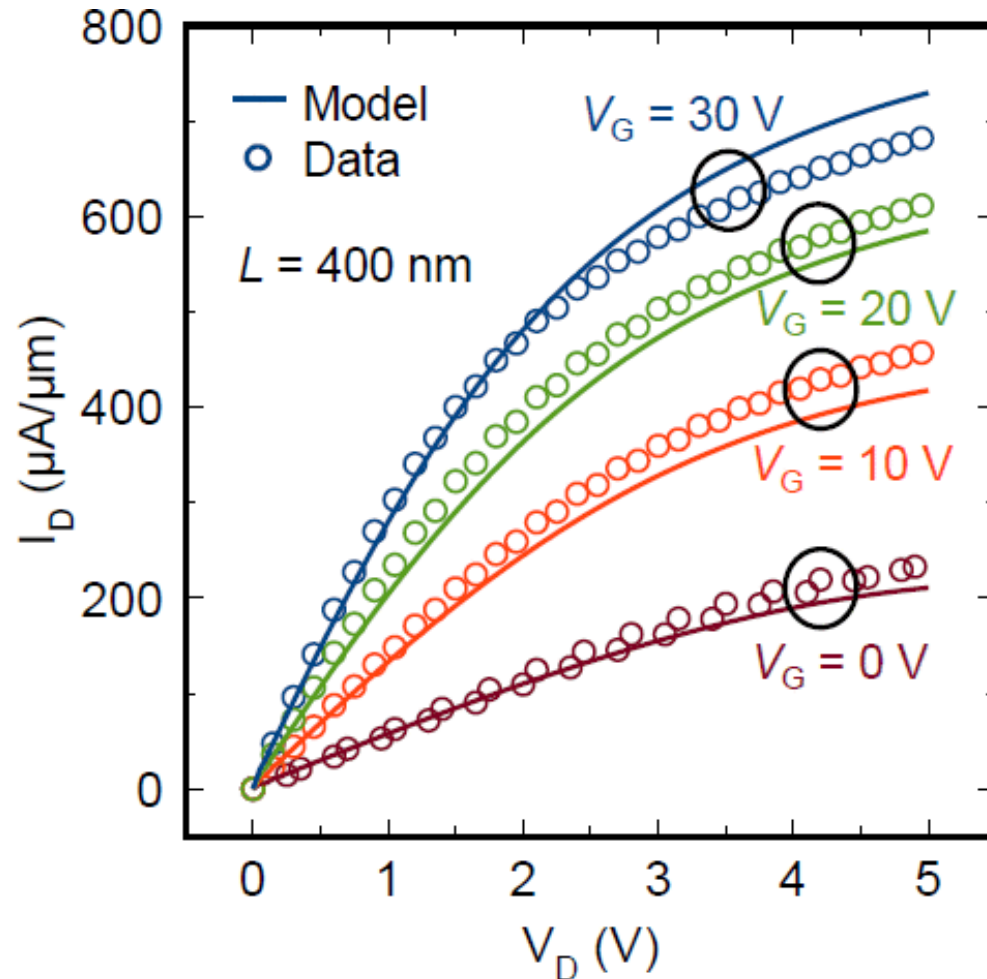


# Progress Towards a Practical Technology



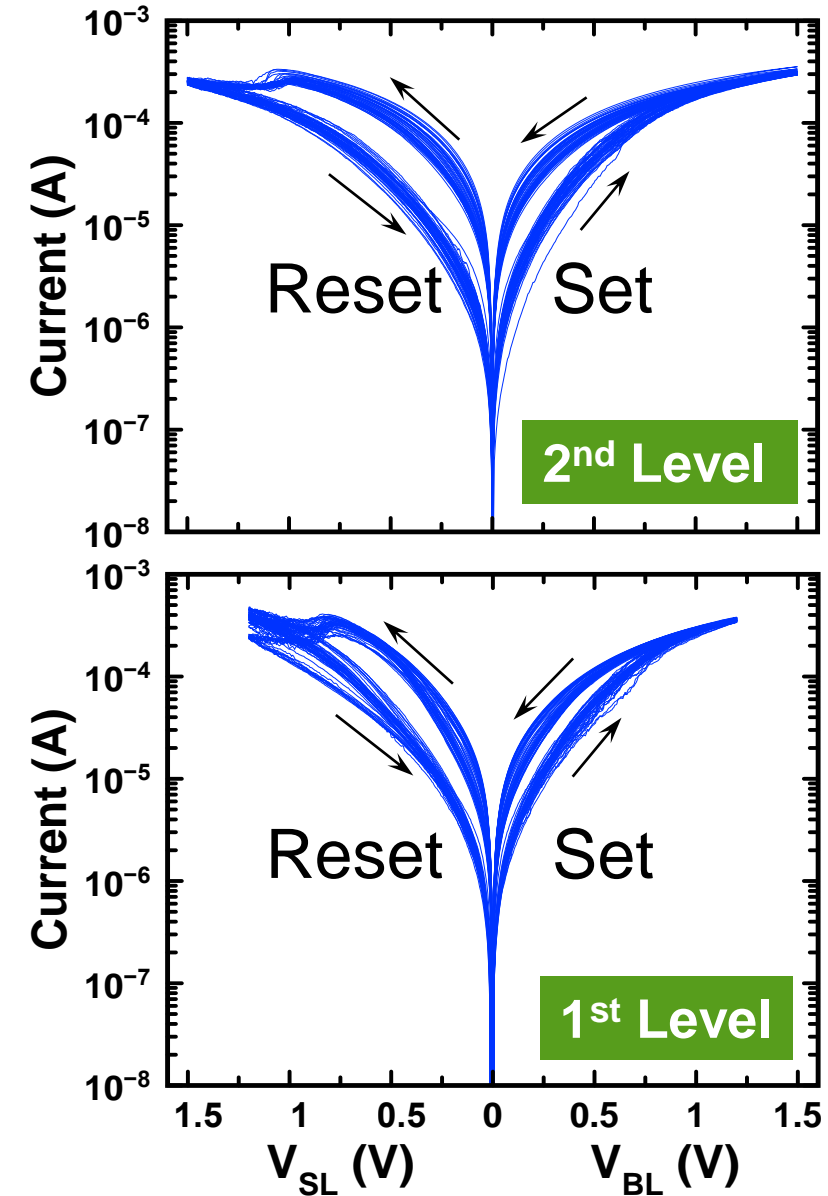
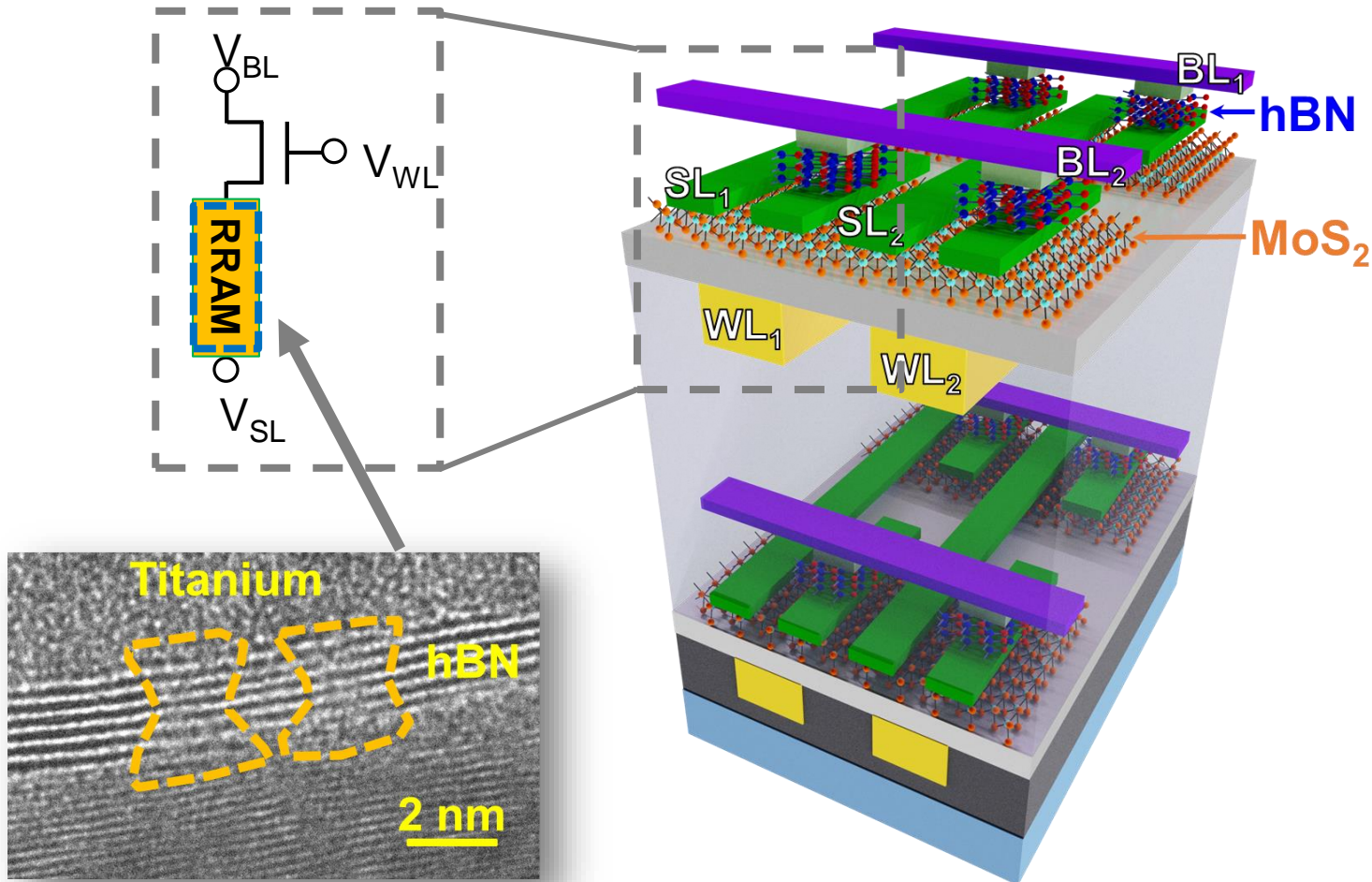
# 1L MoS<sub>2</sub> TRANSISTOR

RECORD:  $I_{ON} = 700 \mu\text{A}/\mu\text{m}$ ,  $R_C = 480 \Omega \cdot \mu\text{m}$



# 3D INTEGRATION:

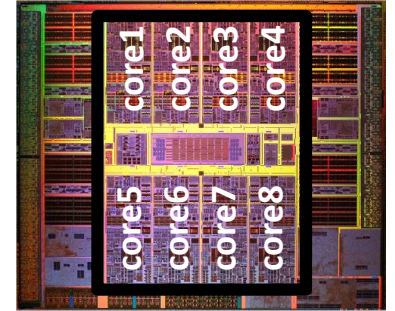
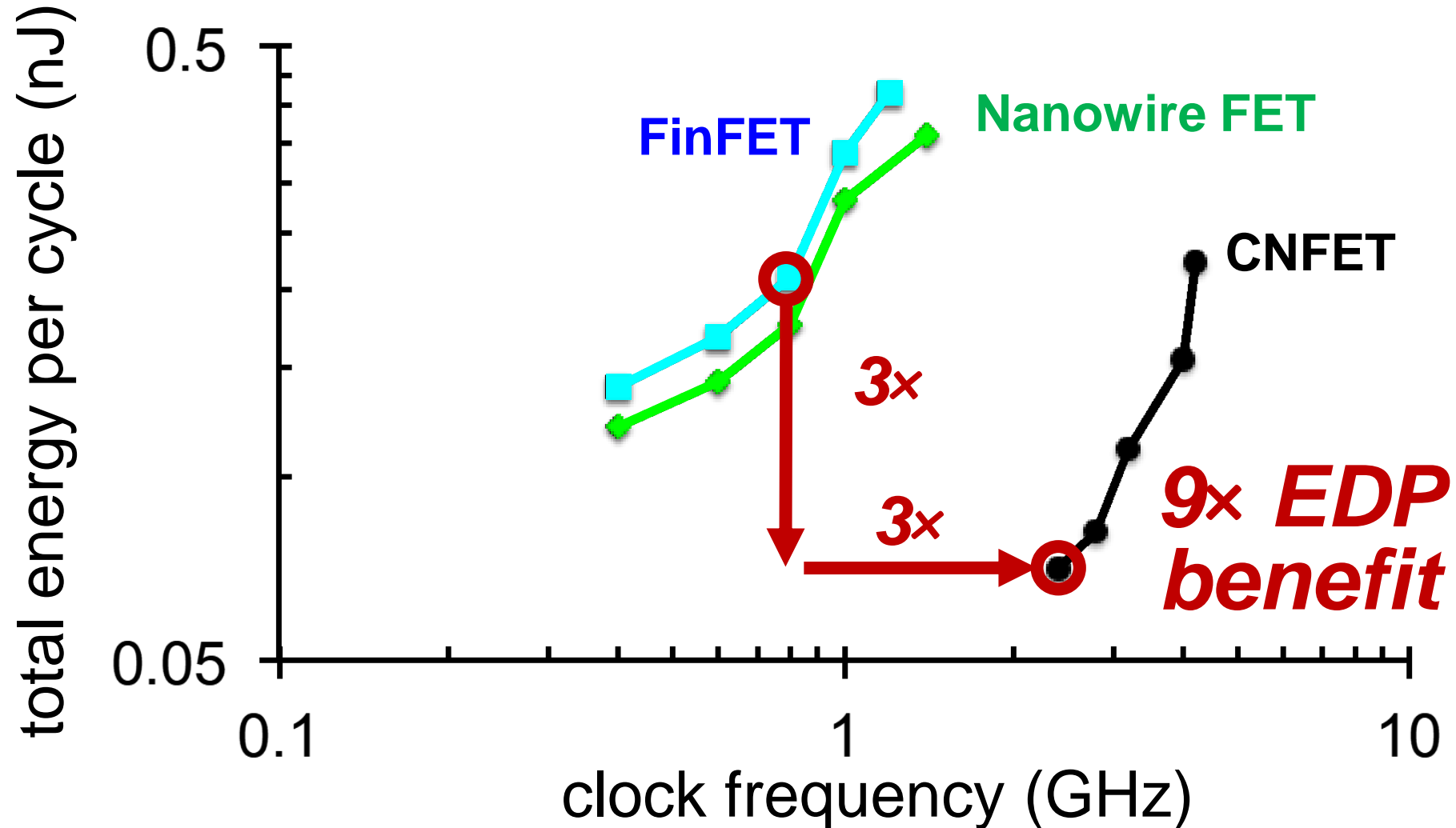
(MoS<sub>2</sub> TRANSISTOR + RRAM) x **2 LAYERS**



Y. Shi, ... E. Pop, H.-S. P. Wong, M. Lanza, *IEDM*, paper 5.4, 2017

# CARBON NANOTUBE TRANSISTOR

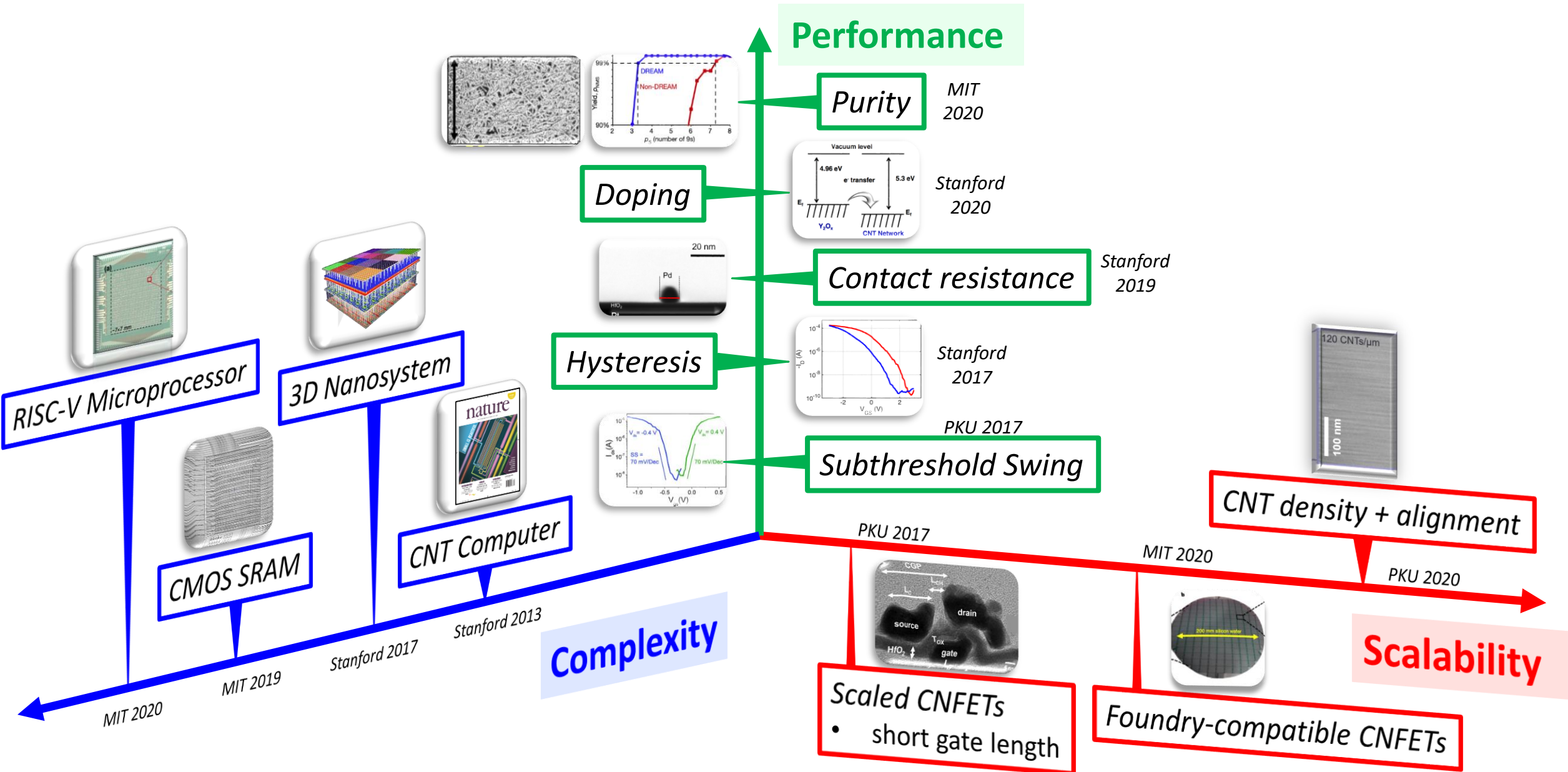
9X BETTER THAN SILICON TRANSISTOR



- OpenSPARC T2 processor core
- full physical design
- 32 million FETs

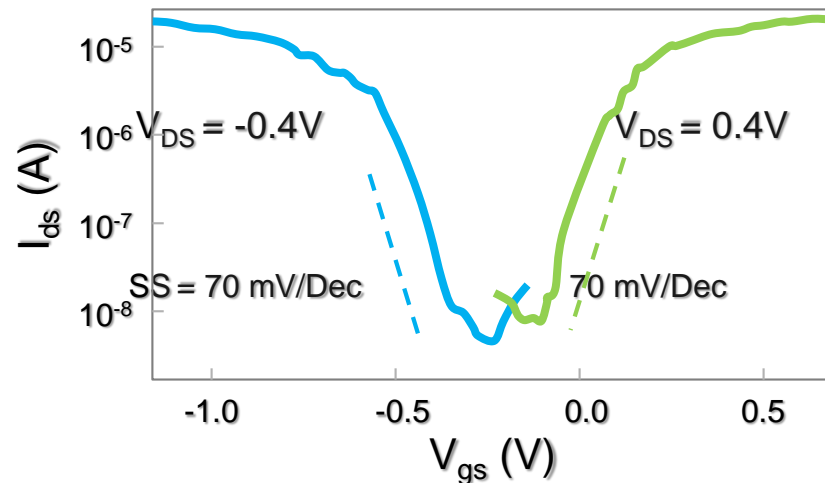
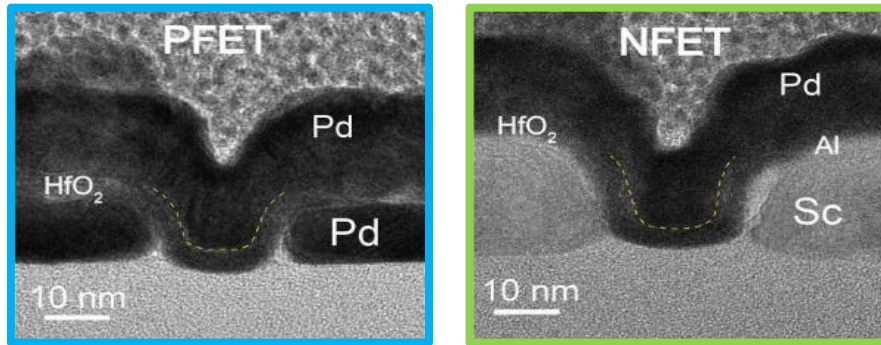


# Progress Towards a Practical Technology

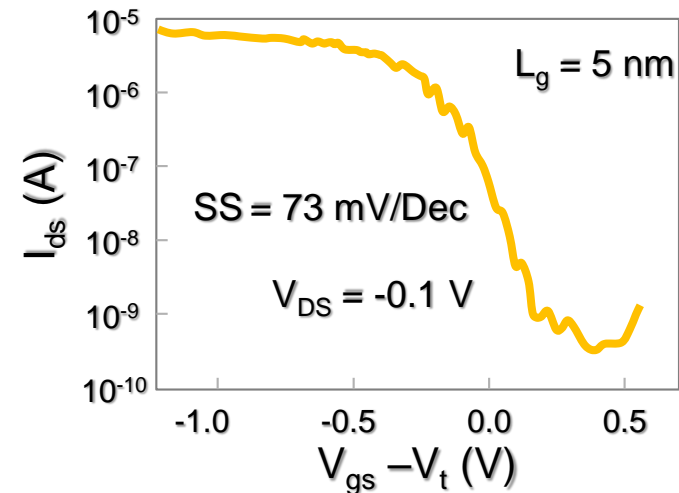
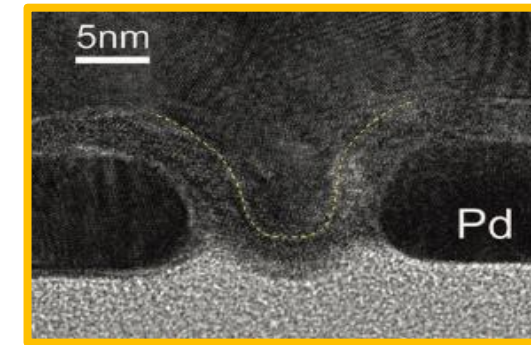


# SHORT-CHANNEL CARBON NANOTUBE TRANSISTORS

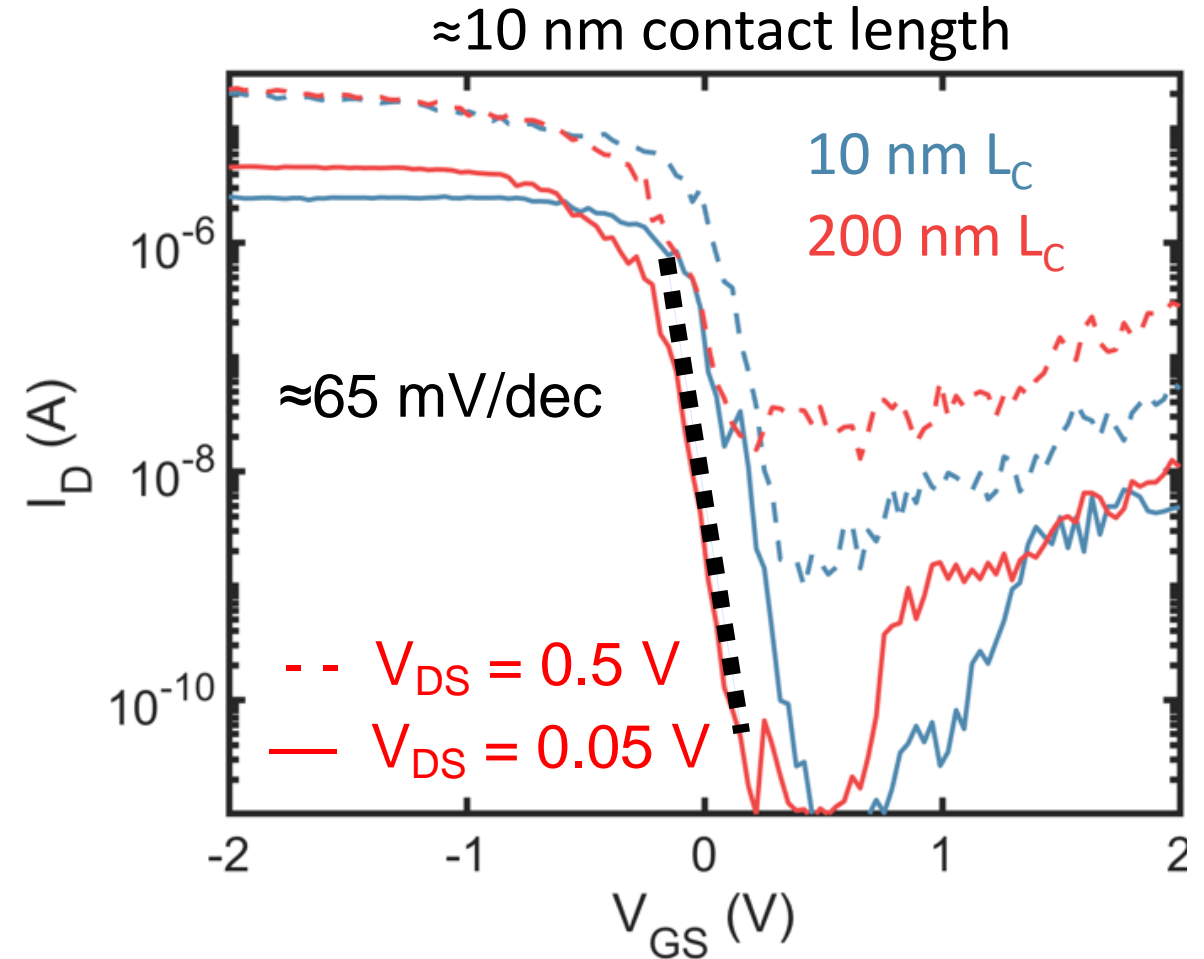
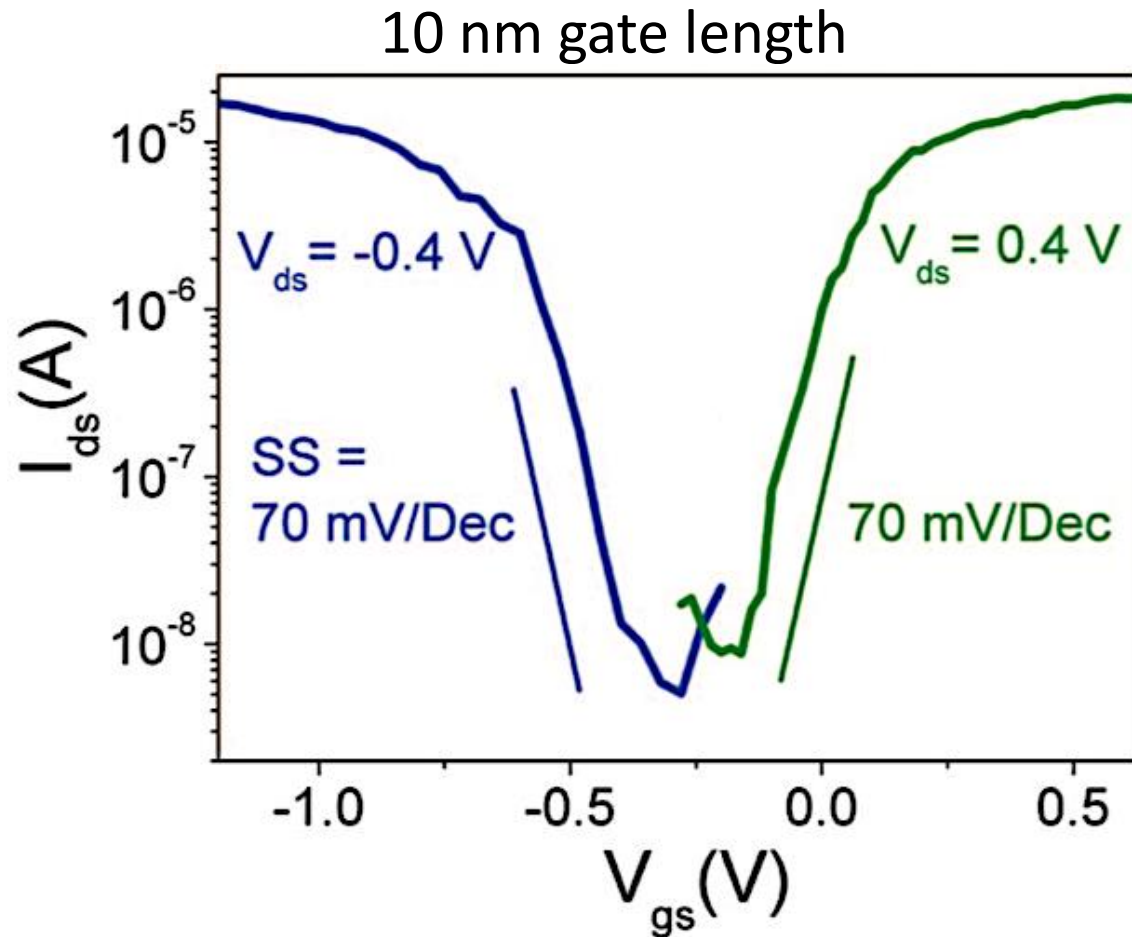
10 nm Gate Length



5 nm Gate Length

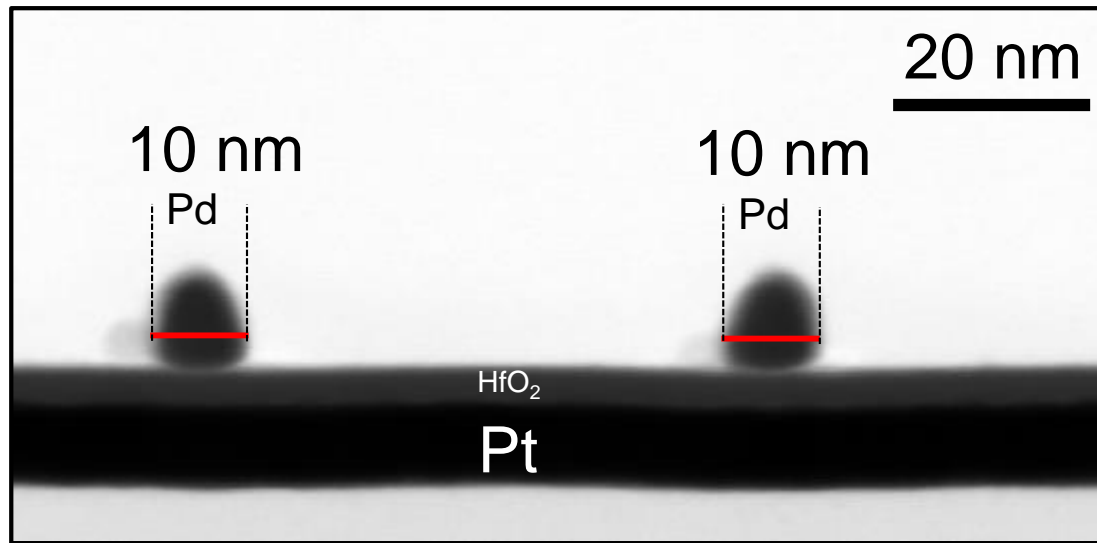


# LOW SUBTHRESHOLD SWING for Low Power

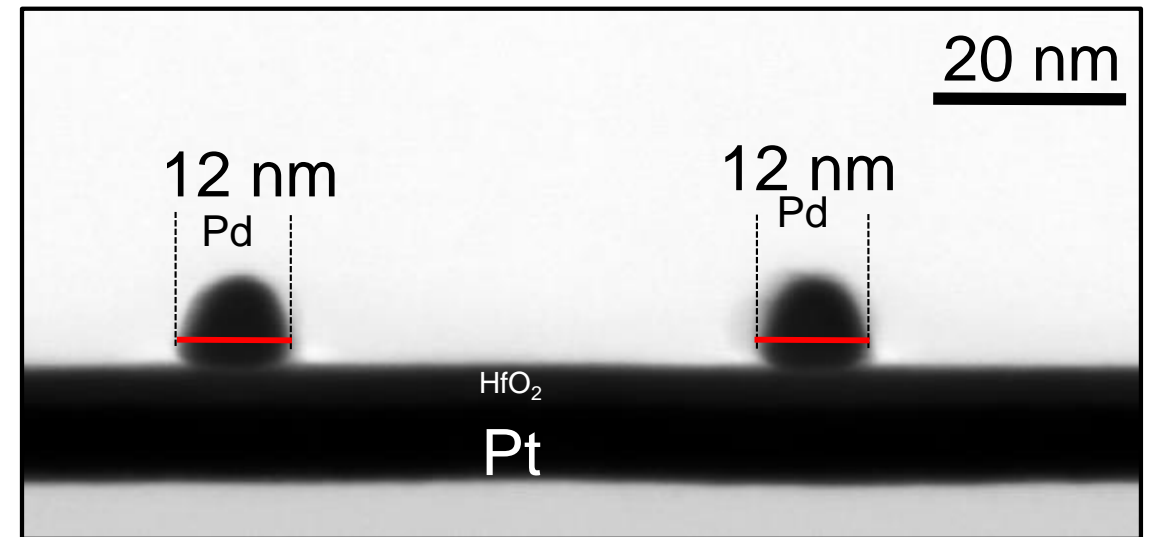


# 10-NM CONTACT TO CARBON NANOTUBE

Measured  $R_C = 7.6 \text{ k}\Omega$



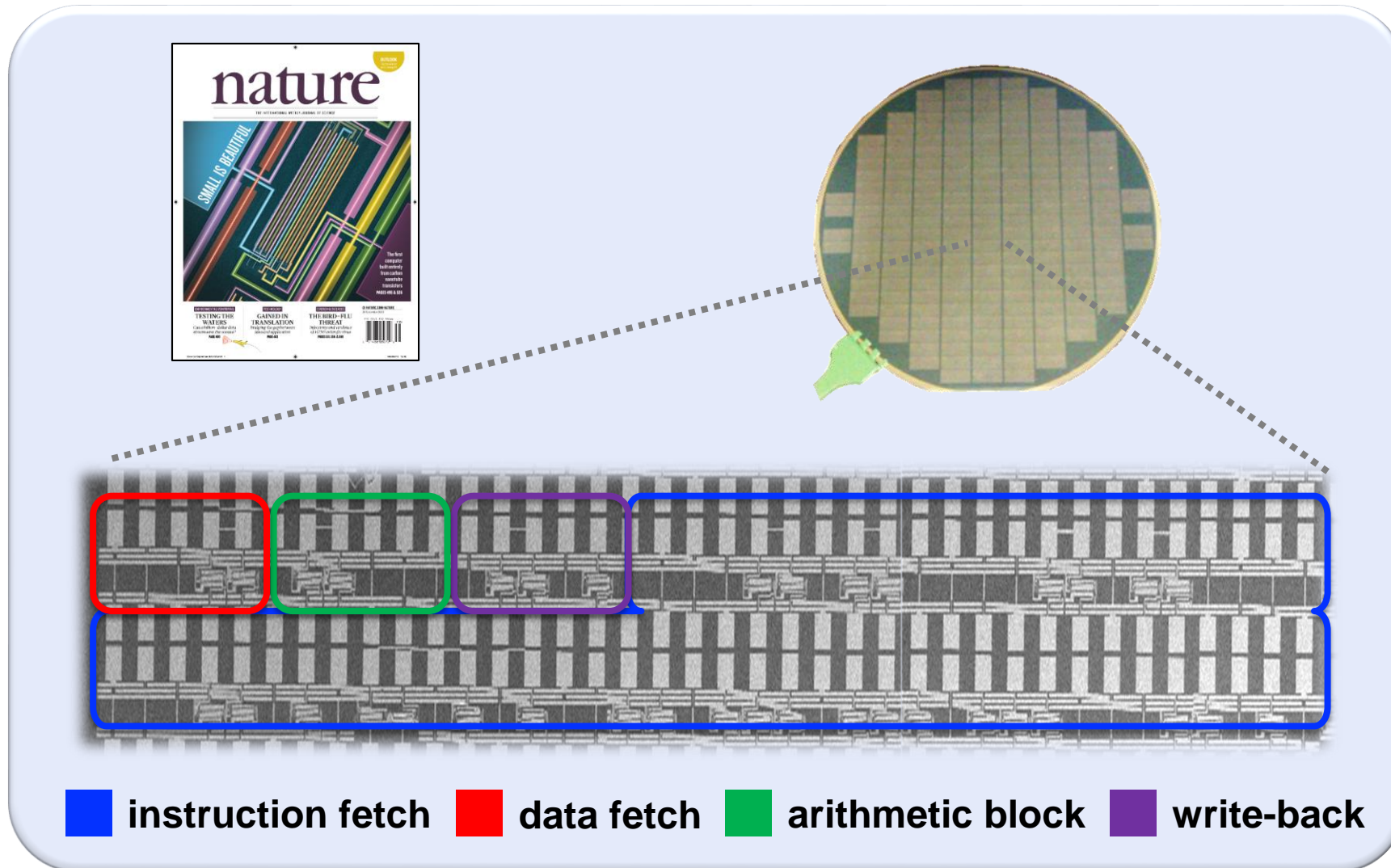
Measured  $R_C = 6.5 \text{ k}\Omega$



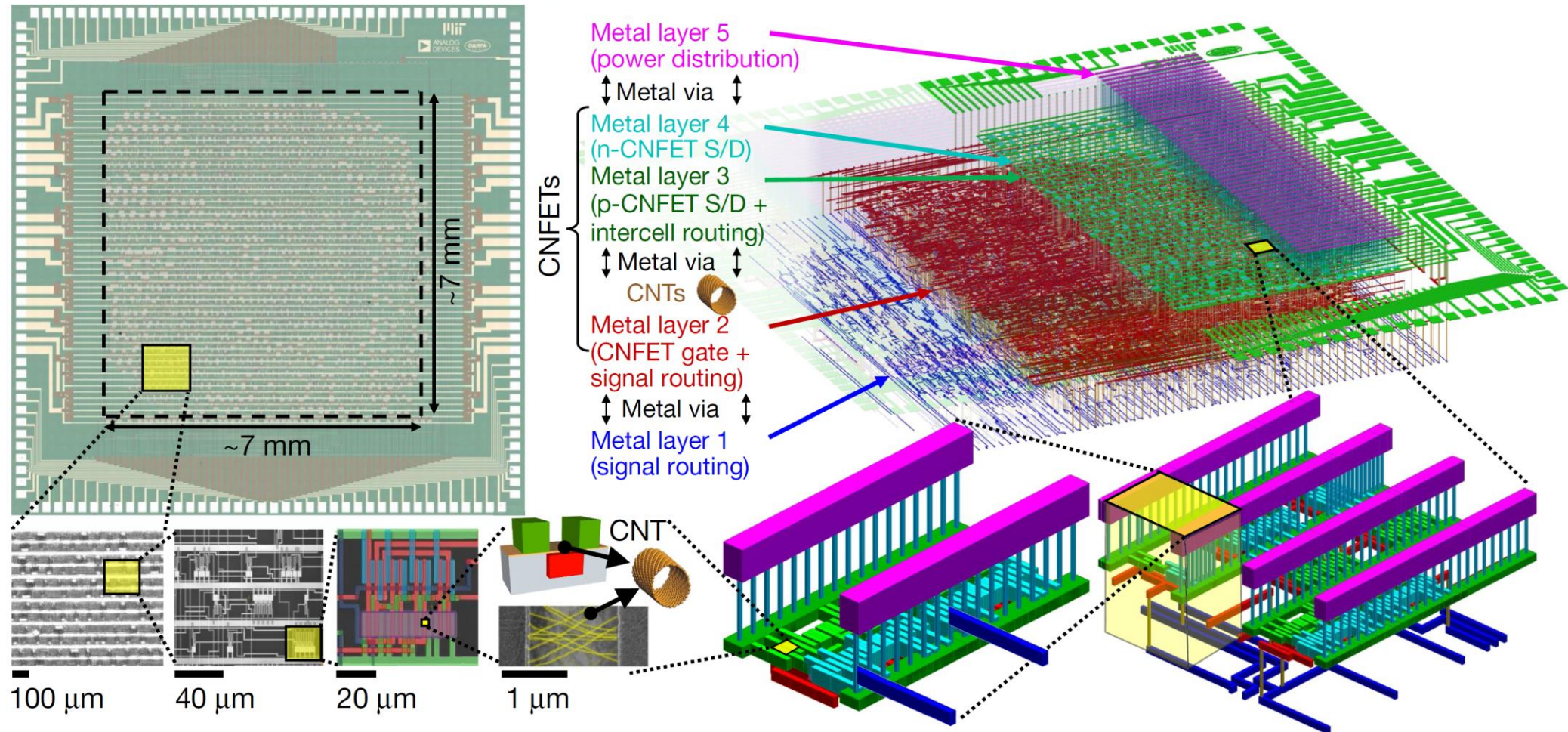
At metal-CNT interface at CNT, the contact dimension is smaller



# NANOSYSTEM: CARBON NANOTUBE COMPUTER



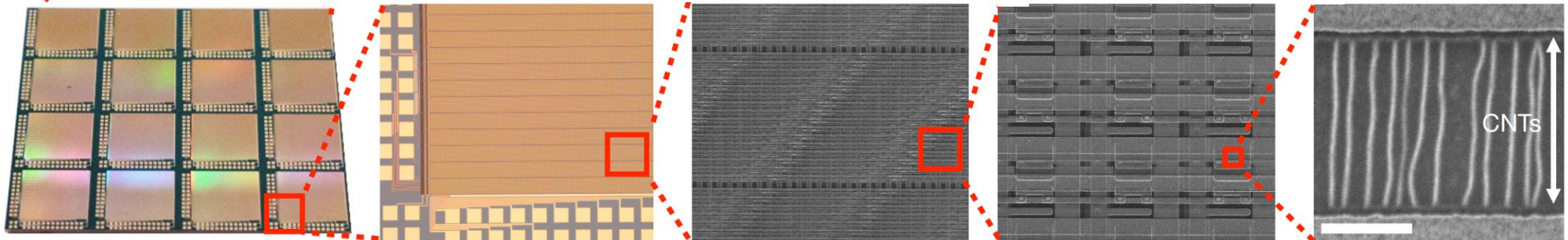
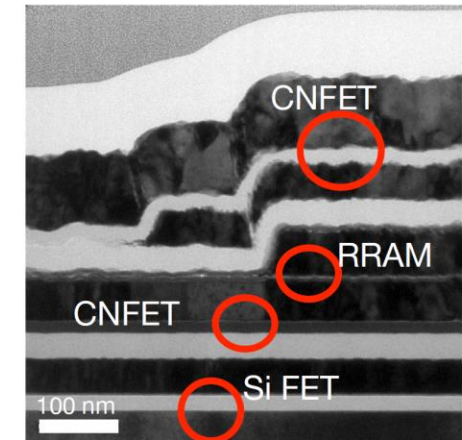
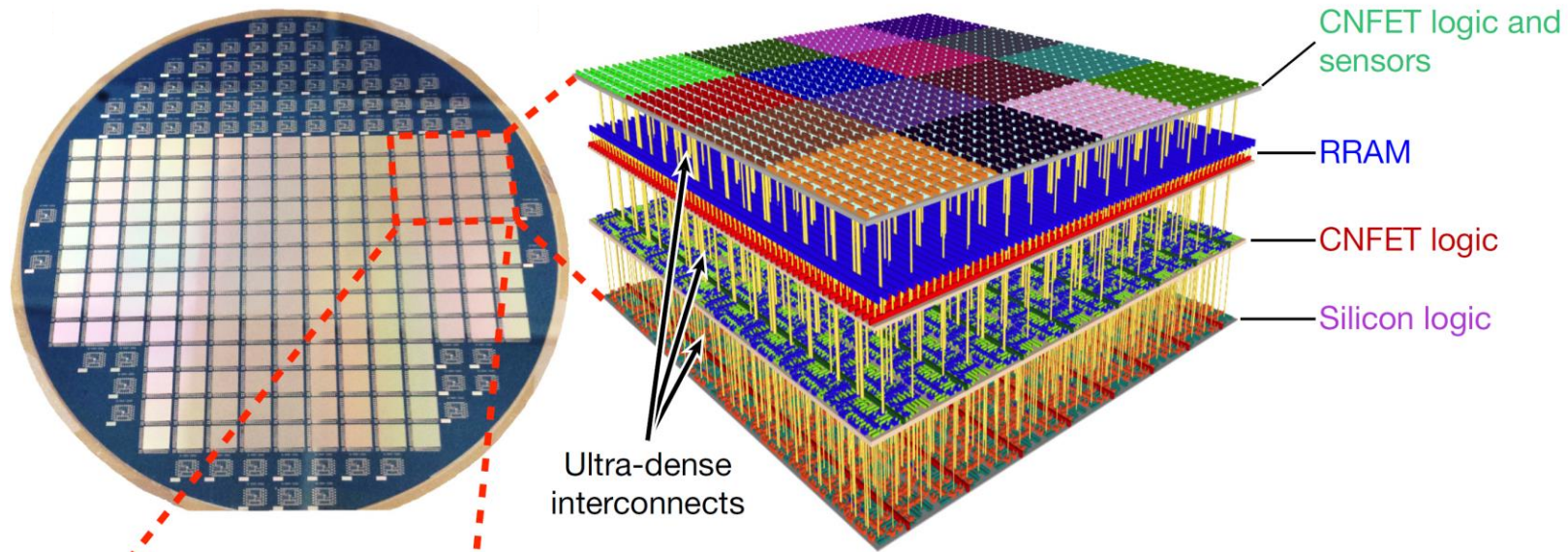
# CARBON NANOTUBE RISC-V PROCESSOR



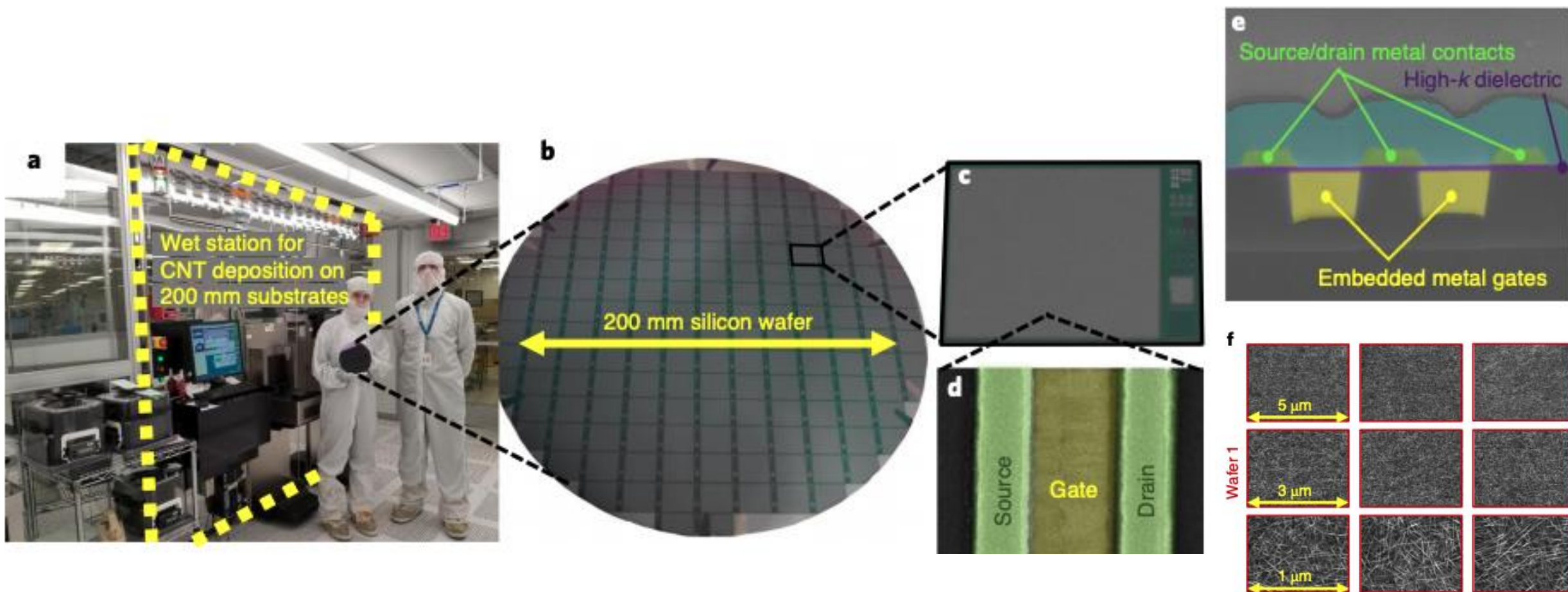


# N3XT NANOSYSTEM

> 2 MILLION CNFETS, 1 MBIT RRAM



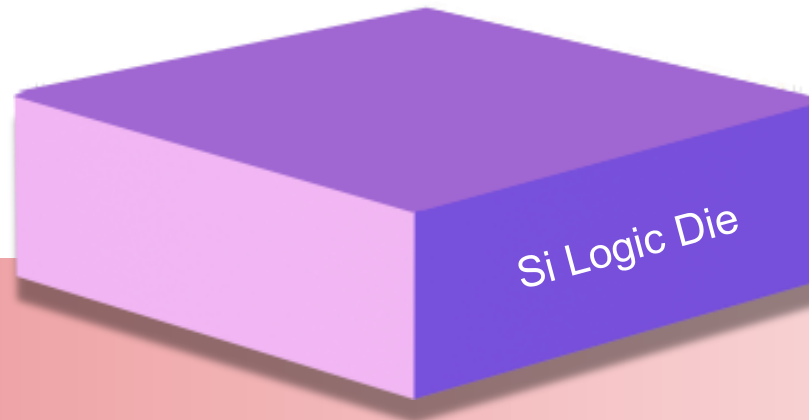
# TRANSLATION TO CHIP FOUNDRY





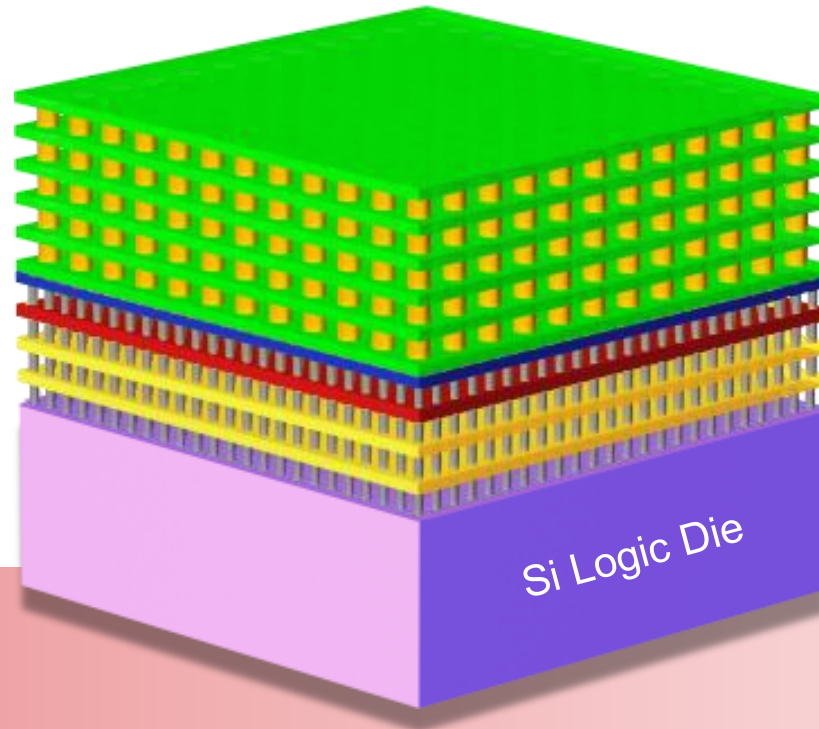
# MEMORY INTEGRATION ON LOGIC PLATFORM

✗ Better transistor alone

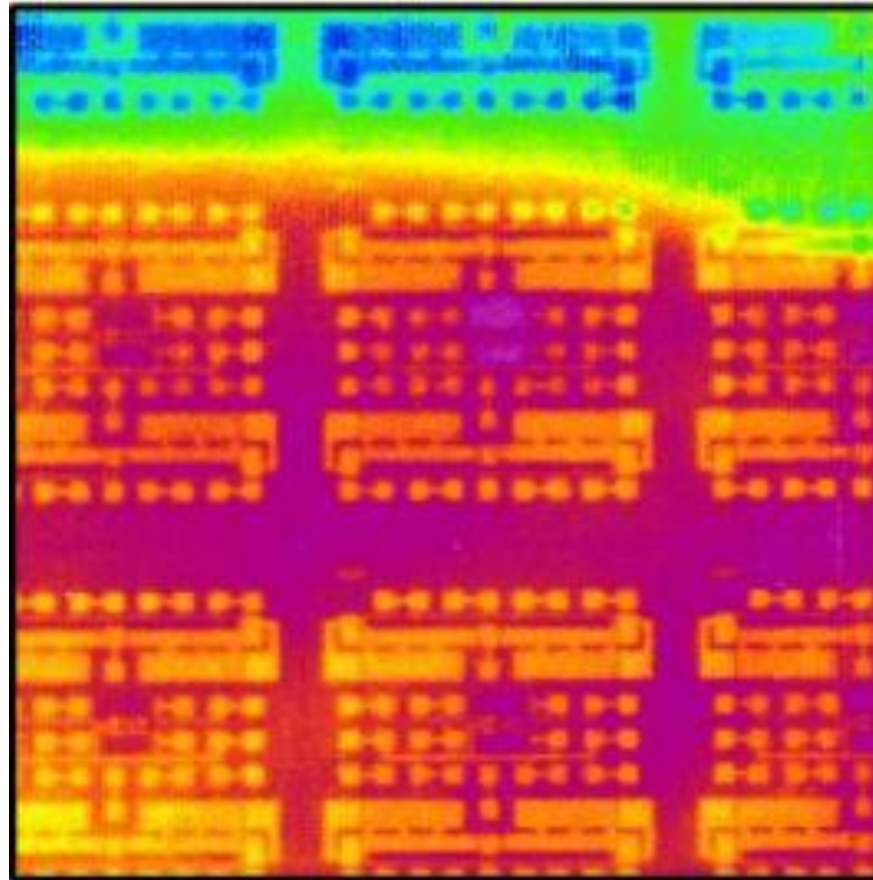


# MEMORY INTEGRATION ON LOGIC PLATFORM

✓ Transistors integrated with memory in **3D**



# THERMAL MANAGEMENT



Hot spot image: Prof. K. Goodson (Stanford)

# N3XT NanoSystem

3D Resistive RAM

Massive storage

1D CNFET, 2D FET

Compute, RAM access

MRAM

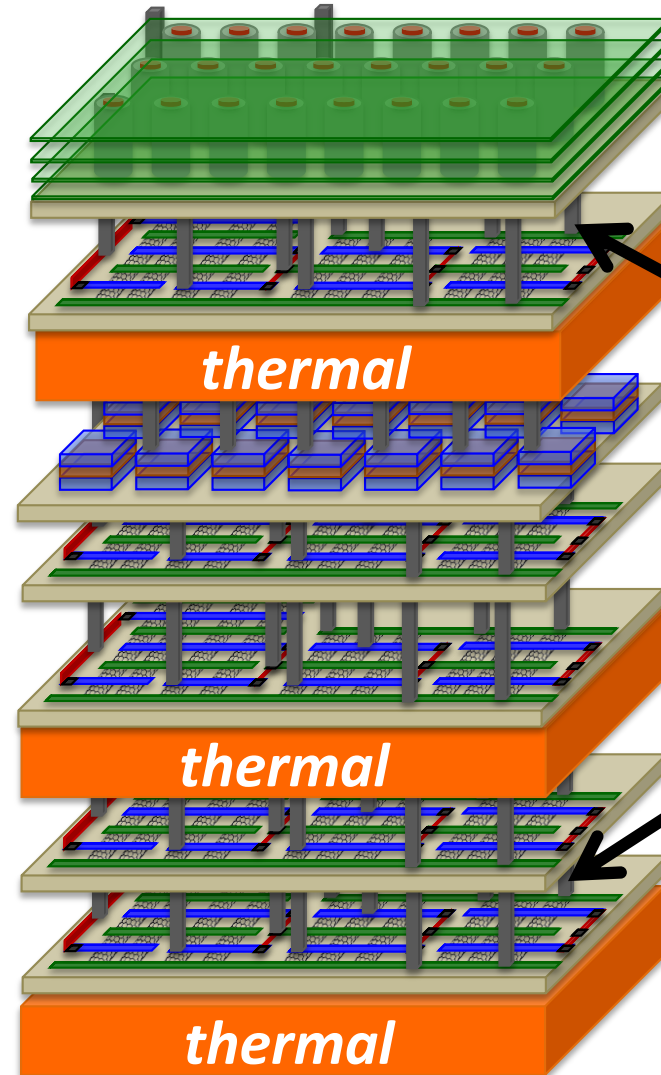
Quick access

1D CNFET, 2D FET

Compute, RAM access

1D CNFET, 2D FET

Compute, Power, Clock



Not TSV

Ultra-dense,  
fine-grained vias

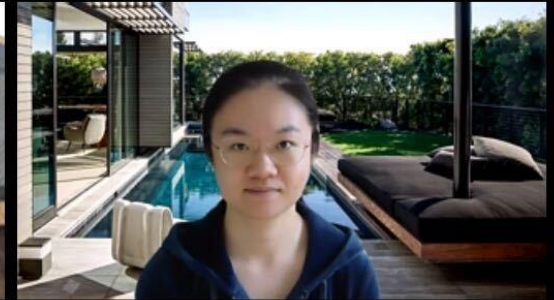
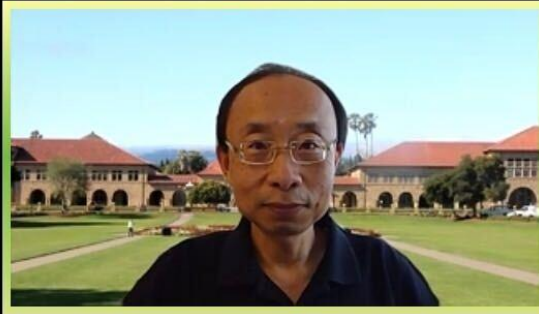
Silicon compatible

M. Aly et al., *IEEE Computer*, 2015





# Students and Post-Docs @ Stanford





# Collaborators



Ken Goodson



Eric Pop



Simon Wong



Mehdi Asheghi

# Collaborators

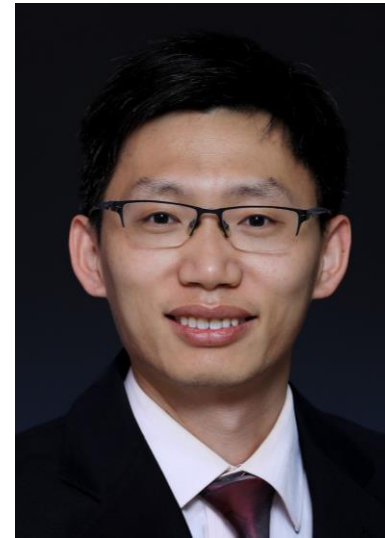
UC San Diego



Gert Cauwenberghs



Huaqiang Wu



Bin Gao



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# Collaborators



Subhasish Mitra



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# Stanford | SystemX Alliance



Agilent Technologies



ON Semiconductor®



# Sponsors

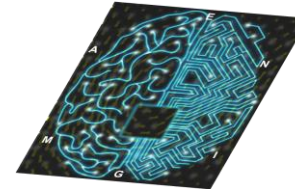


*JUMP*

*ASCENT*



E2CDA - ENIGMA



ERI – 3DSoc

**Stanford** | SystemX Alliance



**Stanford** | Non-Volatile Memory Technology Research Initiative (NMTRI)



End of Talk

Questions?